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(FILE 'HOME' ENTERED AT 11:37:54 ON 03 MAY 2005)
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FILE 'REGISTRY' ENTERED AT 11:38:00 ON 03 MAY 2005
Ll
                   STR
L2
                   SCR 2043
L3
               50 SEA SSS SAM L1 AND L2
            19317 SEA SSS FUL L1 AND L2
L4
                   SAV TEM LA NWA0950FO/A
L<sub>5</sub>
              931 SEA ABB=ON PLU=ON L4 AND C3F60
              582 SEA ABB=ON .PLU=ON L5 AND TRIFLUOROMETHYL
L6
L7
                   STR
L8
                   STR L7
               30 SEA SUB=L4 SSS SAM L8
L9
              654 SEA SUB=L4 SSS FUL L8
L10
                   SAV TEM NWAO950SO/A L10
                   D QUE L10
              152 SEA ABB=ON PLU=ON L10 AND 1(W)2(W)2(W)2 (W)TETRAFLUOROETHYL
L11
              168 SEA ABB=ON PLU=ON L6 AND 1(W)2(W)2(W)2 (W)TETRAFLUOROETHYL
L12
              168 SEA ABB=ON PLU=ON L11 OR L12
L13
      FILE 'HCAPLUS' ENTERED AT 12:15:27 ON 03 MAY 2005
              138 SEA ABB=ON PLU=ON L13
L14
                   E SURFACTANT/CT
                   E SURFACTANTS/CT
                   E E3+ALL
L15
           225071 SEA ABB=ON PLU=ON (SURFACTANTS+OLD, NT OR SURFACE ACTIVITY+OLD
                    NT OR SURFACTANT ADSORPTION OR PENETRATING AGENTS)/CT
               25 SEA ABB=ON PLU=ON L14 AND L15
L16
                   E AUDENAERT F/AU
                  SEA ABB=ON PLU=ON ("AUDENAERT F"/AU OR "AUDENAERT FRANS"/AU
L17
                   OR "AUDENAERT FRANS A"/AU OR "AUDENAERT FRANS ALBERT"/AU)
                   E DAMS R/AU
              238 SEA ABB=ON PLU=ON ("DAMS R"/AU OR "DAMS R A J"/AU)
L18
                   E DAMS RUDOL/AU
               41 SEA ABB=ON PLU=ON ("DAMS RUDOLF"/AU OR "DAMS RUDOLF J"/AU OR "DAMS RUDOLF J E A"/AU OR "DAMS RUDOLF JOZEF"/AU OR "DAMS
L19
                   RUDOLPH J"/AU)
                   E TAN L/AU
              140 SEA ABB=ON PLU=ON ("TAN L"/AU OR "TAN L S"/AU OR "TAN L S K"/AU OR "TAN L SENG"/AU)
L20
                   E TAN LIAN/AU
                                          ("TAN LIAN S"/AU OR "TAN LIAN SOON"/AU)
(3M (1A) INNOV?)/CS, PA
                7 SEA ABB=ON PLU=ON
L21
                                 PLU=ON
L22
             2229 SEA ABB=ON
                2 SEA ABB=ON PLU=ON L16 AND (L17 OR L18 OR L19 OR L20 OR L21
L23
                   OR L22)
               23 SEA ABB=ON PLU=ON L16 NOT L23
L24
=> b reg
FILE 'REGISTRY' ENTERED AT 12:21:47 ON 03 MAY 2005
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STRUCTURE FILE UPDATES: 2 MAY 2005 HIGHEST RN 849658-68-0 DICTIONARY FILE UPDATES: 2 MAY 2005 HIGHEST RN 849658-68-0

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 18, 2005

Please note that search-term pricing does apply when conducting SmartSELECT searches.

\* The CA roles and document type information have been removed from \* \* the IDE default display format and the ED field has been added, \* effective March 20, 2005. A new display format, IDERL, is now \* available and contains the CA role and document type information. 

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at: http://www.cas.org/ONLINE/DBSS/registryss.html

=> d que sta 113 L1



L5

NODE ATTRIBUTES: DEFAULT MLEVEL IS ATOM DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES: RING(S) ARE ISOLATED OR EMBEDDED NUMBER OF NODES IS

STEREO ATTRIBUTES: NONE

SCR 2043 L2

L4

19317 SEA FILE=REGISTRY SSS FUL L1 AND L2
931 SEA FILE=REGISTRY ABB=ON PLU=ON L4 AND C3F60
582 SEA FILE=REGISTRY ABB=ON PLU=ON L5 AND TRIFLUOROMETHYL L6 L8

NODE ATTRIBUTES: DEFAULT MLEVEL IS ATOM DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES: RING(S) ARE ISOLATED OR EMBEDDED NUMBER OF NODES IS 21

STEREO ATTRIBUTES: NONE

654 SEA FILE=REGISTRY SUB=L4 SSS FUL L8 L10

L11 152 SEA FILE=REGISTRY ABB=ON PLU=ON L10 AND 1(W)2(W)2(W)2

(W) TETRAFLUOROETHYL

L12 168 SEA FILE=REGISTRY ABB=ON PLU=ON L6 AND 1 (W) 2 (W) 2 (W) 2

(W) TETRAFLUOROETHYL

L13 168 SEA FILE=REGISTRY ABB=ON PLU=ON L11 OR L12

=> b hcap FILE 'HCAPLUS' ENTERED AT 12:21:59 ON 03 MAY 2005 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

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FILE COVERS 1907 - 3 May 2005 VOL 142 ISS 19 FILE LAST UPDATED: 2 May 2005 (20050502/ED)

New CAS Information Use Policies, enter HELP USAGETERMS for details.

This file contains CAS Registry Numbers for easy and accurate substance identification.

=> d all fhitstr 123 tot

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ANSWER 1 OF 2 HCAPLUS COPYRIGHT 2005 ACS on STN
     2003:417794 HCAPLUS
AN
     139:7655
DN
     Entered STN: 01 Jun 2003
ED
     Compositions for aqueous delivery of fluorinated silanes
TI
     Terrazas, Michael S.; Pellerite, Mark J.; Dams, Rudolf J.
IN
     3M Innovative Properties Company, USA
PA
     PCT Int. Appl., 43 pp.
     CODEN: PIXXD2
DT
     Patent
     English
LA
     ICM C08G065-336
IC
     ICS C08G077-00; C09D183-00
     37-3 (Plastics Manufacture and Processing)
     Section cross-reference(s): 42
FAN. CNT 1
     PATENT NO.
                             KIND
                                    DATE
                                                   APPLICATION NO.
                                                                             DATE
     WO 2003044075
                                     20030530
                                                   WO 2002-US34278
                                                                             20021025
PΙ
                              A1
                                                                           CA, CH, CN,
                            AM, AT, AU,
                                          AZ, BA,
                                                            BR, BY, BZ,
                                                   BB, BG,
          ₩:
              AE, AG, AL,
               CO,
                        CU,
                            CZ,
                                 DE.
                                      DK,
                                          DM,
                                               DZ,
                                                   EC,
                                                        EE,
                                                             ES,
                                                                 FI,
                                                                      GB,
                                                                           GD, GE, GH,
                   CR,
                            ID,
                                IL,
                                                                           LC, LK, LR,
               GM, HR,
                       HU,
                                      IN,
                                          IS,
                                               JP,
                                                   KE,
                                                            KP,
                                                                 KR,
                                                                      KZ,
                                                        KG,
               LS, LT,
                        LU,
                            LV, MA,
                                     MD,
                                          MG, MK, MN, MW,
                                                             MX,
                                                                 MZ,
                                                                      NO,
                                                                           NZ,
                                                                               OM, PH,
                       RO,
                            RU,
                                 SD,
                                          SG,
               PL, PT,
                                     SE,
                                               SI,
                                                   SK, SL,
                                                            TJ,
                                                                 TM,
                                                                      TN.
                                                                           TR,
                                               ZM,
               UA,
                   UG,
                        UZ,
                             VC,
                                 VN,
                                      YU,
                                          ZA,
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                                 MW,
          RW: GH, GM,
                       KE,
                            LS,
                                      MZ,
                                          SD,
                                               SL,
                                                   SZ,
                                                             UG.
                                                                           AM, AZ, BY,
                       MD, RU,
                                               BE, BG, CH, CY,
                                                                 CZ, DE,
                                                                           DK, EE, ES,
               KG, KZ,
                                 TJ,
                                     TM,
                                          AT,
                                                   NL,
                                 IE,
                                     IT,
                                          LU,
                                                        PT,
                                                             SE,
               FI, FR,
                       GB.
                            GR,
                                               MC,
                                                                 SK,
                                                                      TR,
                                                                           BF, BJ, CF,
               CG,
                   CI,
                       CM,
                            GA,
                                 GN,
                                     GQ,
                                          GW,
                                               ML,
                                                   MR, NE, SN, TD,
                                                                     TG
                                                  US 2001-2543
     US 6592659
                                     20030715
                                                                             20011115
                              B1
                                                                             20021025
     EP 1444290
                                     20040811
                                                  EP 2002-776307
                              A1
                                DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK
              AT, BE, CH, DE, IE, SI, LT, LV,
                                                                             20021025
      JP 2005509708
                              T2
                                     20050414
                                                   JP 2003-545709
PRAI US 2001-2543
                                     20011115
     WO 2002-US34278
                                     20021025
CLASS
 PATENT NO.
                   CLASS
                           PATENT FAMILY CLASSIFICATION CODES
 WO 2003044075
                   ICM
                            C08G065-336
                            C08G077-00; C09D183-00
                   ICS
                            106/287.130; 106/287.140; 106/287.270; 427/387.000;
 US 6592659
                   NCL
                            428/421.000; 428/447.000
                           4H020/BA11; 4H020/BA21; 4H020/BA23; 4H020/BA36;
4J002/BQ002; 4J002/CH052; 4J002/CP081; 4J002/CP181;
4J002/EF006; 4J002/EN006; 4J002/EV286; 4J002/FD312;
                   FTERM
 JP 2005509708
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4J002/FD316; 4J002/GH01; 4J005/AA04; 4J005/BD05;
                          4J005/BD08; 4J038/CG032; 4J038/CG142; 4J038/CH262; 4J038/CJ252; 4J038/DF011; 4J038/DF012; 4J038/DL051;
                          4J038/DL061; 4J038/DL161; 4J038/GA02; 4J038/GA06;
                          4J038/GA09; 4J038/GA12; 4J038/GA13; 4J038/HA156; 4J038/KA09; 4J038/MA07; 4J038/MA08; 4J038/MA09;
                          4J038/NA07
     The invention relates to a dilutable, nonaq. concentrate and an aqueous dilution used
AB
     for aqueous delivery of fluorinated silanes to a substrate, a method of
     treating a substrate with the aqueous dilution composition to render it oil and water
     repellent, and articles having coatings made from the aqueous dilution The aqueous
     dilution may be coated on a substrate to provide a durable coating. Thus,
     shaking 5.0 g a 10% solution of Krytox 157FS(L) (carboxy group-containing
     fluoropolymer) ammonium salt in MeOH with 1.0 g trimethoxysilylpropylamido group-terminated perfluorinated polyether (I) gave a single-phase liquid
     containing 16.7% I. Diluting 0.5 g the concentrated solution above with 10.0 g water gave
     a clear dilution with no precipitation
     silane deriv perfluorinated polyether ag conc diln surface treatment
     Ceramics
     Coating materials
         (dilutable concs. for aqueous delivery of fluorinated silanes)
IT
     Glass, miscellaneous
     RL: MSC (Miscellaneous)
         (dilutable concs. for aqueous delivery of fluorinated silanes)
IT
     Surfactants
         (fluorosurfactants; dilutable concs. for aqueous delivery of fluorinated
        silanes)
IT
     Polyethers, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
         (perfluoro, silylated; dilutable concs. for aqueous delivery of fluorinated
         silanes)
IT
     Fluoropolymers, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
         (polyether-, perfluoro, silylated; dilutable concs. for aqueous delivery of
         fluorinated silanes)
IT
     101947-16-4
                    220864-25-5
                                    233676-28-3
     RL: TEM (Technical or engineered material use); USES (Uses)
         (surface treatment; dilutable concs. for aqueous delivery of fluorinated
     30136-13-1, Dowanol PnP
                                 68259-10-9 126600-08-6, KRYTOX
ΙT
     157FS(L) ammonium salt
     RL: MOA (Modifier or additive use); USES (Uses)
         (surfactant; dilutable concs. for aqueous delivery of fluorinated silanes)
RE. CNT
               THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD
(1) Du Pont; EP 0611771 A 1995 HCAPLUS
   Du Pont; WO 9523804 A 1995 HCAPLUS
(3) Minnesota Mining & Mfg; EP 0611771 A 1994 HCAPLUS
(4) Minnesota Mining & Mfg; EP 0611771 A 1997 HCAPLUS
(5) Minnesota Mining & Mfg; WO 9723432 A 1997 HCAPLUS
     126600-08-6, KRYTOX 157FS(L) ammonium salt
     RL: MOA (Modifier or additive use); USES (Uses) (surfactant; dilutable concs. for aqueous delivery of fluorinated silanes)
     126600-08-6 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-w-(heptafluoropropoxy)-, ammonium salt
     (9CI) (CA INDEX NAME)
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ANSWER 2 OF 2 HCAPLUS COPYRIGHT 2005 ACS on STN
     2002:849502 HCAPLUS
AN
     137:354443
DN
ED
     Entered STN: 08 Nov 2002
ΤI
     Dispersant in non-polar solvent
     Rao, Prabhakara S.
IN
     3M Innovative Properties Company, USA
PA
S<sub>0</sub>
     PCT Int. Appl., 19 pp.
     CODEN: PIXXD2
DT
     Patent
     English
     ICM B01F017-00
     ICS
          C08J003-09; C08F002-14; G02F001-167
     42-7 (Coatings, Inks, and Related Products)
FAN. CNT 1
     PATENT NO.
                            KIND
                                   DATE
                                                 APPLICATION NO.
                                                                           DATE
     WO 2002087738
                                    20021107
                                                 WO 2002-US2343
                                                                           20020125
PΙ
                             A1
             AE, AG, AL,
                           AM, AT,
                                    AU,
                                                 BB, BG, BR, BY, BZ, CA, CH, CN,
          ₩:
                                        AZ, BA,
                                    DK,
                                                                             GE, GH,
              CO, CR,
                       CU, CZ, DE,
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                                                  EC,
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                               IL,
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                       HU,
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                                         IS,
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              GM, HR,
                           ID,
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              LS,
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                   LT,
                       LU,
                           LV,
                                MA,
                                    MD,
                                             MK,
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              PL, PT,
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              UA, UG,
                       UZ,
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                               YU,
                                         ZM,
                                             ZW, AM, AZ,
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                                                           BY, KG, KZ,
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                                    MZ,
                                             SL,
                                                               ZM,
         RW: GH, GM,
                       KE,
                           LS,
                               MW,
                                         SD.
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                      DK,
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              CY,
                   DE,
                           ES,
                                    FR,
                                                  IE,
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                           CG,
                               CI, CM, GA,
                                                 GQ, GW, ML, MR,
                                                                             TD, TG
              BF,
                 BJ,
                       CF,
                                             GN,
                                                                    NE,
                                                                        SN,
                                                 US 2001-837784
     US 2003018111
                                    20030123
                                                                           20010418
                             A1
     US 6562889
                                    20030513
                             B2
     EP 1392421
                                    20040303
                                                 EP 2002-704258
                                                                           20020125
                             A1
          R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
                  SI, LT, LV, FI, RO, MK, CY, AL,
                                                      TR
     JP 2004536899
                             T2
                                    20041209
                                                 JP 2002-585072
                                                                           20020125
                                    20010418
PRAI US 2001-837784
                             A
     WO 2002-US2343
                                    20020125
CLASS
                          PATENT FAMILY CLASSIFICATION CODES
 PATENT NO.
                   CLASS
 WO 2002087738
                   ICM
                           B01F017-00
                          C08J003-09; C08F002-14; G02F001-167
524/366.000; 524/319.000
                   ICS
 US 2003018111
                   NCL
                   ECLA
                          B01F017/00H; C08J003/09; G02F001/167
                          4D077/AA01; 4D077/AB03; 4D077/AC05; 4D077/DD29Y; 4D077/DE10Y; 4D077/DE35Y; 4J002/BC07W; 4J002/BG04W; 4J002/CH02X; 4J002/EB066; 4J002/FD090; 4J002/FD31X;
 JP 2004536899
                   FTERM
                           4J002/GQ00
AB
     The present invention provides a stable, non-film-forming dispersion
     comprising (a) dispersed particles, (b) a liquid non-polar solvent which is preferably fluorinated, and (c) a dispersant selected from the group
     consisting of highly fluorinated polyethers, having an atomic ratio of carbon
     to oxygen of between 2 and 4 inclusive, and bearing at least one polar
     functional group which is preferably an ionizable group such as a
     carboxylic acid group. The dispersants are suitable for dispersing
     pigments in paints.
     pigment dispersant non polar solvent
     Perfluoro compounds
     RL: TEM (Technical or engineered material use); USES (Uses)
         (C5-18, dispersant in non-polar solvent for pigments)
IT
     Carbon black, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
         (Raven 1200; dispersant in non-polar solvent for pigments)
     Dispersing agents
IΤ
     Pigments, nonbiological
         (dispersant in non-polar solvent for pigments)
ΙT
     Polyethers, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
         (fluorinated; dispersant in non-polar solvent for pigments)
IT
         (nonpolar, fluorinated; dispersant in non-polar solvent for pigments)
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Alkanes, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
          (perfluorinated, solvent; dispersant in non-polar solvent for pigments)
     147-14-8, Spectra Pac C Blue 15:4
     RL: TEM (Technical or engineered material use); USES (Uses)
         (Cyan PB, Spectra Pac C Blue 15:4; dispersant in non-polar solvent for
         pigments)
     5567-15-7
     RL: TEM (Technical or engineered material use); USES (Uses)
     (PY 83 Yellow; dispersant in non-polar solvent for pigments)
98-08-8, Oxsol 2000 106-91-2, Glycidyl methacrylate 1047-16-1,
Monastral Red B-RT 796D 1319-73-9, Methylstyrene 5888-33-5, Isobornyl
                  26570-48-9, Polyethylene glycol diacrylate
                                                                        32724-62-2,
     Solvent Blue 97 51601-43-5, Zirconium Ten-Cem 51798-33-5, Krytox 157FSH 90317-74-1, Krytox 157FSL 106441-58-1, Krytox 157FSM
     RL: TEM (Technical or engineered material use); USES (Uses)
         (dispersant in non-polar solvent for pigments)
                THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
    John, I; WO 9967297 A 1999 HCAPLUS
(1)
    Nippon Mektron Kk; JP 62200335 A
Wei-Hsin, H; US 5573711 A 1996 HCAPLUS
     90317-74-1, Krytox 157FSL
     RL: TEM (Technical or engineered material use); USES (Uses)
         (dispersant in non-polar solvent for pigments)
     90317-74-1 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX
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$$F-CF_2-CO_2H$$
 $G=CO_2H$ 
 $G=CO_2H$ 

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=> d all hitstr 124 tot
     ANSWER 1 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
L24
      2005:101411 HCAPLUS
AN
DN
      142:337067
      Entered STN: 07 Feb 2005
ED
     Polymer encapsulation of fine particles by a supercritical antisolvent
      Wang, Yulu; Pfeffer, Robert; Dave, Rajesh; Enick, Robert
     New Jersey Center for Engineered Particulates, New Jersey Institute of
CS
      Technology, Newark, NJ, 07102, USA
     AICHE Journal (2005), 51(2), 440-455
CODEN: AICEAC; ISSN: 0001-1541
S<sub>0</sub>
     John Wiley & Sons, Inc.
DT
      Journal
LA
     English
CC
     37-6 (Plastics Manufacture and Processing)
      Section cross-reference(s): 46
     Coating and encapsulation of fine particles with polymer using a
     supercrit. antisolvent (SAS) coating process was investigated in this research. Synthesized submicron silica particles were used as host
      particles and poly(lactide-co-glycolide) (PLGA), a biodegradable polymer
      used for controlled release of drugs, was chosen as the coating material.
      In the SAS coating process a suspension of silica particles in an
      acetone-polymer solution was sprayed through a capillary nozzle into
      supercrit. (SC) CO2, which acts as an antisolvent for the acetone.
     rapid mutual diffusion between the SC CO2 and the acetone causes supersatn. of the polymer solution, leading to nucleation and precipitation of the
      polymer to encapsulate the silica particles. The operating parameters
      that have an effect on the coating process, such as polymer to particle
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weight ratio, polymer concentration, temperature, pressure, flow rate of polymer solution,

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and the addition of a SC CO2 soluble surfactant, were systematically studied.
      It is shown that the polymer to silica ratio and the polymer concentration are
      critical for the successful encapsulation of silica particles with min.
      agglomeration.
      lactide glycolide copolymer silica particle encapsulation surfactant
      supercrit antisolvent
      Solvents
          (antisolvents; poly(lactide-glycolide) encapsulation of fine silica
         particles by supercrit. antisolvent process)
IT
     Flow
          (effect on poly(lactide-glycolide) encapsulation of fine silica
         particles by supercrit. antisolvent process)
IT
     Polyoxyalkylenes, uses
      RL: NUU (Other use, unclassified); USES (Uses)
          (fluorine-containing, surfactant; for poly(lactide-glycolide) encapsulation
         of fine silica particles by supercrit. antisolvent process)
     Surfactants
ΙT
          (for poly(lactide-glycolide) encapsulation of fine silica particles by
         supercrit. antisolvent process)
     Agglomeration
      Encapsulation
      Particle size
      Particle size distribution
      Particles
      Solubility
      Supercritical fluids
      Ternary phase diagram
          (poly(lactide-glycolide) encapsulation of fine silica particles by
         supercrit. antisolvent process)
      Polyesters, properties
      RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP
      (Physical process); PROC (Process)
          (poly(lactide-glycolide) encapsulation of fine silica particles by
         supercrit. antisolvent process)
     Fluoropolymers, uses
      RL: NUU (Other use, unclassified); USES (Uses)
         (polyoxyalkylene-, surfactant; for poly(lactide-glycolide) encapsulation of fine silica particles by supercrit. antisolvent
         process)
ΙT
     Fluoropolymers, uses
      RL: NUU (Other use, unclassified); USES (Uses)
          (surfactant; for poly(lactide-glycolide) encapsulation of fine silica
         particles by supercrit. antisolvent process)
     7631-86-9, Silica, properties 26780-50-7, Resomer RG 502
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
ΙT
          (poly(lactide-glycolide) encapsulation of fine silica particles by
         supercrit. antisolvent process)
     67-64-1, Acetone, uses
RL: NUU (Other use, unclassified); USES (Uses)
          (solvent; poly(lactide-glycolide) encapsulation of fine silica
         particles by supercrit. antisolvent process)
IΤ
      124-38-9, Carbon dioxide, uses
      RL: NUU (Other use, unclassified); USES (Uses)
          (supercrit. fluid; poly(lactide-glycolide) encapsulation of fine silica
     particles by supercrit. antisolvent process) 74049-08-4, 3, 3, 4, 4, 5, 5, 6, 6, 7, 7, 8, 8, 9, 9, 10, 10, 10-Heptadecafluorodecyl
      acrylate homopolymer 90317-74-1, Krytox 157FSL 97002-50-1,
      3, 3, 4, 4, 5, 5, 6, 6, 7, 7, 8, 8, 9, 9, 10, 10, 10-Heptadecafluorodecyl acrylate-styrene
      RL: NUU (Other use, unclassified); USES (Uses)
          (surfactant; for poly(lactide-glycolide) encapsulation of fine silica
         particles by supercrit. antisolvent process)
37 THERE ARE 37 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE. CNT
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(3) Chang, C; AIChE J 1989, V35, P1876 HCAPLUS
(4) Chang, C; AIChE J 1990, V36, P939 HCAPLUS
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 (7) Davies, R; Adv Mater 1998, V10, P1264 HCAPLUS
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(17) O'Neill, M; Ind Eng Chem Res 1998, V37, P3067 HCAPLUS
(18) Peng, D; Ind Eng Chem Fundam 1976, V15, P59 HCAPLUS (19) Pessey, V; Ind Eng Chem Res 2000, V39, P4714 HCAPLUS (20) Pessey, V; J Alloys Compd 2001, V323, P412
 (21) Randolph, T; Biotechnol Prog 1993, V9, P429 HCAPLUS
(22) Reverchon, E; Ind Eng Chem Res 1998, V37, P952 HCAPLUS
(23) Shaffer, K; Macromolecules 1996, V29, P2704 HCAPLUS
(24) Shiho, H; Macromolecules 2000, V33, P1565 HCAPLUS
(25) Soppimath, K; J Microencapsul 2001, V18, P397 HCAPLUS
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(27) Tom, J; Biotechnol Prog 1991, V7, P403 HCAPLUS
(28) Tom, J; J Supercrit Fluids 1994, V7, P9 HCAPLUS
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(29) Tu, L; Powder Technol 2002, V126, P134 HCAPLUS
       Walas, S; Phase Equilibria in Chemical Engineering, chap 2 1985
       Wang, D; J Controlled Release 1999, V57, P9 HCAPLUS Wang, Y; J Supercrit Fluids 2004, V28, P85 HCAPLUS
       Wang, Y; Powder Technol 2002, V127, P32 HCAPLUS
       Xu, J; SPE J 2003, V8, P85 HCAPLUS
       Yates, M; Macromolecules 1999, V32, P1018 HCAPLUS
Yeo, S; Biotechnol Bioeng 1993, V41, P341 HCAPLUS
(36)
       Young, T; J Pharm Sci 1999, V88, P640 HCAPLUS
(37)
       90317-74-1, Krytox 157FSL
       RL: NUU (Other use, unclassified); USES (Uses)
             (surfactant; for poly(lactide-glycolide) encapsulation of fine silica
            particles by supercrit. antisolvent process)
       90317-74-1 HCAPLUS
CN
       Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
       1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX
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$$F-CF_2-CO_2H$$
 0-  $(C_3F_6)$  0-  $(CF_2)_3-F$ 

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ANSWER 2 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
     2004:1154601 HCAPLUS
AN
DN
     142:76555
ED
     Entered STN: 30 Dec 2004
ΤI
     Process for recovery of surfactants
IN
     Nagai, Takabumi; Fujii, Kazuhisa; Asai, Hideaki
PA
     Daikin Industries, Ltd., Japan
S<sub>0</sub>
     PCT Int. Appl., 26 pp.
     CODEN: PIXXD2
DT
     Patent
      Japanese
     ICM B01J015-00
     ICS B01J003-00
     45-5 (Industrial Organic Chemicals, Leather, Fats, and Waxes)
     Section cross-reference(s): 46, 74, 76
FAN. CNT 1
     PATENT NO.
                                                  APPLICATION NO.
                            KIND
                                    DATE
                                                                             DATE
                             A1
PΙ
     WO 2004112952
                                    20041229
                                                  WO 2004-JP8967
                                                                             20040618
          W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, F1, GB, GD,
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GE, GH, GM, HR, HU, ID,
                                        IL, IN,
                          LT,
                               LU,
                                   LV,
                                                              MW,
                                            MD,
                                                 MG, MK,
                                                          MN,
                                                                  ΜX,
                                                                       MZ,
                                                                           NA, NI,
              LK, LR, LS,
                                        MA,
              NO,
                  NZ,
                       OM,
                           PG,
                               PH,
                                    PL,
                                        PT,
                                             RO,
                                                 RU,
                                                      SC,
                                                          SD,
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                                                                   SG,
                                                                       SK,
                                            UG,
                                                 US,
                                                     UZ,
                                                          VC.
                                                              VN,
                                                                  YU, ZA,
                  TM,
                      TN,
                           TR,
                               TT,
              TJ,
                                   TZ,
                                        UA,
         RW: BW, GH, GM, KE, LS,
                                    MW,
                                        MZ, NA, SD,
                                                     SL,
                                                          SZ,
                                                              TZ, UG, ZM,
                                                                           ZW,
                      KG, KZ, MD,
                                    RU,
                                        TJ, TM, AT, BE, BG,
                                                              CH, CY,
                                                                       CZ,
                                                                           DE,
                                                                               DK,
              AZ,
                  BY,
                      FI, FR, GB, GR,
TR, BF, BJ, CF,
              EE,
                  ES,
                                        HU,
                                            IE,
                                                 IT,
                                                     LU,
                                                          MC,
                                                              NL,
                                                                  PL,
                                                                       PT,
                                                                           RO,
                                        CG, CI, CM, GA, GN, GQ, GW, ML,
              SI,
                  SK,
              SN, TD, TG
PRAI JP 2003-176139
                                   20030620
                            A
CLASS
 PATENT NO.
                  CLASS
                         PATENT FAMILY CLASSIFICATION CODES
 WO 2004112952
                  ICM
                          B01J015-00
                          B01J003-00
                  ICS
     A process for recovering a surfactant (e.g., a fluorosurfactant) from a
AB
     H20-C02 system containing ≥1 surfactant comprises bringing the system
     into contact with a dehydrating agent to thereby remove the water and recover the surfactant. The process is characterized by circulating a mixed system containing CO2, a CO2-compatible surfactant and/or co-solvent,
     and a subject of removal in a circulation line provided with a
     selective-removal device for the subject of removal to remove selectively
     the subject of removal taken in the surfactant and/or the co-solvent. The
     surfactant-containing system is used in cleaning or drying of semiconductor
     wafers, photoresists, precision devices, clothing, etc.
     fluorosurfactant recovery carbon dioxide water system; photoresist
     cleaning surfactant recovery carbon dioxide water system
IT
     Supercritical fluids
         (carbon dioxide; process for recovery of surfactants from water-carbon
        dioxide system)
ΙT
     Molecular sieves
         (dehydrating agent; process for recovery of surfactants from
        water-carbon dioxide system)
IT
     Silica gel, uses
     RL: NUU (Other use, unclassified); USES (Uses)
         (dehydrating agent; process for recovery of surfactants from
        water-carbon dioxide system)
IT
     Surfactants
         (fluorosurfactants; process for recovery of surfactants from
        water-carbon dioxide system)
IT
     Semiconductor materials
         (process for recovery of surfactants from water-carbon dioxide system)
IT
     Textiles
         (process for recovery of surfactants from water-carbon dioxide system
        in cleaning of cloth)
IT
     Photoresists
         (process for recovery of surfactants from water-carbon dioxide system
        in cleaning of photoresists)
                                       69431-33-0, Amberlite IR 400
IT
     39288-70-5, Amberlite IR 122
     RL: NUU (Other use, unclassified); USES (Uses)
         (adsorbents; process for recovery of surfactants from water-carbon
        dioxide system)
     124-38-9, Carbon dioxide, uses
     RL: NUU (Other use, unclassified); USES (Uses)
         (process for recovery of surfactants from water-carbon dioxide system) 08-51-8P 62037-80-3P 340034-67-5P
     37208-51-8P
     RL: PEP (Physical, engineering or chemical process); PUR (Purification or
     recovery); PYP (Physical process); PREP (Preparation); PROC (Process)
         (process for recovery of surfactants from water-carbon dioxide system)
               THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE. CNT
RE
    3m Innovative Properties Co; WO 200036272 Al 2002
    3m Innovative Properties Co; JP 2002543241 A 2002
3m Innovative Properties Co; US 6235701 B1 2002 HCAPLUS
(4) Director General Of National Institute Of Advanced Industrial Science And
    Technology; JP 2001247519 A 2001 HCAPLUS
(5) Director General Of National Institute Of Advanced Industrial Science And
    Technology; US 200125121 A1 2001
   Japan Tobacco Inc; JP 06-114202 A 1994 HCAPLUS
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(7) Nippon Telegraph And Telephone Corp; JP 2000138156 A 2000 HCAPLUS

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(8) Nippon Telegraph And Telephone Corp; US 2002132192 A1 2000 HCAPLUS
(9) Nippon Telegraph And Telephone Corp; EP 992852 A2 2000 HCAPLUS
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RL: PEP (Physical, engineering or chemical process); PUR (Purification or recovery); PYP (Physical process); PREP (Preparation); PROC (Process) (process for recovery of surfactants from water-carbon dioxide system) 37208-51-8 HCAPLUS

Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-1, 2, 2, 2-tetrafluoroethyl)- $\omega$ -(heptafluoropropoxy)-, ester with  $\alpha$ -hydro- $\omega$ -methoxypoly(oxy-1, 2-ethanediyl) (9CI) (CA INDEX NAME)

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ANSWER 3 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
L24
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2004:551036 HCAPLUS AN

DN . 141:90923

Entered STN: 09 Jul 2004 ED

Dry cleaning process using composition containing organic dry cleaning solvents and acid surfactants

Evers, Johannes Maria Wilhelmus; Goedhart, Machiel; Kerpels; Freddie; Van IN Kralingen, Cornelis Gerhard; Overdevest, Pieter Everhardus Maria; Reinhoudt, Hank Robert; Vrieswijk, Karin Unilever N.V., Neth.; Unilever PLC; Hindustan Lever Limited

PCT Int. Appl., 43 pp. CODEN: PIXXD2

DT Patent

English LA

ICM D06L001-12

D06L001-22 ICS

46-5 (Surface Active Agents and Detergents)

	PA	TENT :	NO.			KIND		DATE			APPLICATION NO.						DATE			
ΡI	WO	0 2004057093				A1		2004	0708		WO 2003-EP13			573						
		W:	AE,	AG,	AL,	AM,	AT,	AU,	AZ,	BA,	BB,	BG,	BR,	BY,	BZ,	CA,	CH,	CN,		
			CO,					DK,												
			GH,	GM,	HR,	HU,	ID,	IL,	IN,	IS,	JP,	KE,	KG,	KP,	KR,	KZ,	LC,	LK,		
			LR,					MA,												
			OM,	PG,	PH,	PL,	PT,	R0,	RU,	SC,	SD,	SE,	SG,	SK,	SL,	SY,	TJ,	TM,		
			TN,					UG,												
		RW:	BW,	GH,	GM,	KE,	LS,	MW,	MZ,	SD,	SL,	SZ,	TZ,	UG,	ZM,	Z₩,	AM,	ΑZ,		
			BY,	KG,				TJ,												
			ES,	FI,	FR,	GB,	GR,	HÜ,	IE,	IT,	LU,	MC,	NL,	PT,	RO,	SE,	SI,	SK,		
			TR,	BF,	BJ,	CF,	CG,	CI,	CM,	GA,	GN,	GQ,	GW,	ML,	MR,	NE,	SN,	TD,	TG	
PRAI	EP	2002	-804	66		A		2002	1219											
<b>CLAS</b>	S																			
PAT	ENT	NO.		CLA	SS	PATE	NT F	AMIL	Y CL	ASSI	FICA	TION	COD	ES						

WO 2004057093 ICM D06L001-12 **ICS** D06L001-22

A dry cleaning process for in-home dry cleaning comprises a dry cleaning step of contacting a laundry article stained with particulate soil with a dry cleaning composition wherein the liquor to cloth ratio (weight/weight) (LCR) is at most 20, and wherein the composition comprises (A) a non-flammable, non-chlorine containing organic dry cleaning solvent; (B) a cleaning effective amount an acid surfactant. Thus, a low-aqueous dry cleaning composition was prepared by mixing HFE 7200 (Et nonafluorobutyl ether) with 0.1 wt% of Krytox 157FSL (fluorosurfactant) and 0.25 wt% of water. Then, a dry cleaning process was carried out by contracting laundry articles with the dry cleaning compns. and agitated for 15 min at 20° using a liquid to cloth ratio of 13.

ST dry cleaning process compn org solvent acid surfactant

Surfactants

```
(anionic; production of dry cleaning process using composition containing organic dry
        cleaning solvents and acid surfactants)
IT
     Surfactants
         (fluorosurfactants; production of dry cleaning process using composition containing
        organic dry cleaning solvents and acid surfactants)
ΙT
     Cleaning solvents
     Dry cleaning
         (production of dry cleaning process using composition containing organic dry cleaning
         solvents and acid surfactants)
     714252-37-6, Crodafos 810A
     RL: TEM (Technical or engineered material use); USES (Uses)
         (anionic surfactant; production of dry cleaning process using composition containing
        organic dry cleaning solvents and acid surfactants)
     141-62-8, Decamethyl tetrasiloxane 141-63-9, Dodecamethyl pentasiloxane 541-02-6, Decamethyl cyclopentasiloxane 556-67-2,
     Octamethylcyclotetrasiloxane 51000-94-3, Decafluoropentane
     163702-05-4, HFE 7200
219484-64-7, HFE 7100
                               163702-07-6, Nonafluorobutyl methyl ether
     RL: TEM (Technical or engineered material use); USES (Uses)
         (dry cleaning solvent; production of dry cleaning process using composition
     containing organic dry cleaning solvents and acid surfactants) 90317-74-1, Krytox 157FSL 99637-22-6, Zonyl UR
     RL: TEM (Technical or engineered material use); USES (Uses)
         (fluorosurfactant; production of dry cleaning process using composition containing
        organic dry cleaning solvents and acid surfactants)
               THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE. CNT
RE
(1) 3m Innovative Properties Co; WO 0036206 A 2000 HCAPLUS
(2) Gen Electric; WO 0246517 A 2002
(3) Gen Electric; WO 0250366 A 2002
(4) Giampalmi, J; US 3689211 A 1972
(5) Unilever Plc; WO 02053824 A 2002
     90317-74-1, Krytox 157FSL
     RL: TEM (Technical or engineered material use); USES (Uses)
         (fluorosurfactant; production of dry cleaning process using composition containing
        organic dry cleaning solvents and acid surfactants)
     90317-74-1 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], \alpha-(1-carboxy-
CN
```

$$F-CF_2-CO_2H$$
  $O-(C_3F_6)$   $O-(CF_2)_3-F$ 

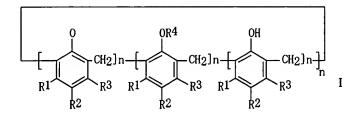
NAME)

```
ANSWER 4 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
     2004:466835 HCAPLUS
AN
DN
     141:38453
ED
     Entered STN: 10 Jun 2004
     Preparation of fluorine-containing calixarenes, compounds with
ΤI
     carbonaceous materials, and their uses
IN
     Furukawa, Miho; Yasuda, Naoki; Idekura, Takateru
     Ajinomoto Co., Inc., Japan
PA
S0
     Jpn. Kokai Tokkyo Koho, 38 pp.
     CODEN: JKXXAF
DT
     Patent
LA
     Tapanese
     ICM C07C043-23
         C07F009-659
     ICS
     25-29 (Benzene, Its Derivatives, and Condensed Benzenoid Compounds)
FAN. CNT 1
     PATENT NO.
                                             APPLICATION NO.
                         KIND
                                DATE
                                                                     DATE
     JP 2004161696
                          A2
                                 20040610
                                             JP 2002-330692
                                                                     20021114
PRAI JP 2002-330692
                                 20021114
CLASS
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1, 2, 2, 2-tetrafluoroethyl)-\overline{\text{-}}(heptafluoropropoxy)- (9CI) (CA INDEX

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PATENT NO. CLASS PATENT FAMILY CLASSIFICATION CODES

JP 2004161696 ICM C07C043-23
ICS C07F009-659
JP 2004161696 FTERM 4H006/AA01; 4H006/AB90; 4H006/GN05; 4H006/GP03; 4H050/AA01; 4H050/AA03; 4H050/AB90; 4H050/AC40
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AB Calixarenes, useful for dispersing or solubilizing carbonaceous materials, e.g. fullerenes, C nanotubes, etc., in fluorocarbon solvents and lubricants, have the following characteristics: (A) ≥1 of the phenolic OH groups is unsubstituted and (B) ≥1 of the phenolic OH groups is substituted with C≥10 group having ≥1 fluoroalkyleneoxy and/or fluorohydrocarbyl. Also claimed are compds. of the calixarenes with carbonaceous materials, and dispersing agents, solubilizing agents, and wetting agents containing the calixarenes. Demnum SA 1 [CF3 (C3F60) k (CF2) 2CH2OH] was reacted with NaH in THF and the reaction mixture was further treated with hexachlorocyclotriphosphazene and 4-tert-butyl-calix(8) arene to give I [R1 = R3 = H; R2 = CMe3, R4 = II [1 of A1-A5 = OCH2 (CF2) 2 (OC3F6) 12.7CF3 and the others = Cl], m = 1, n = approx. 0, 1 = 7, m + n + 1 = 8] (III). Twenty parts of III was dissolved in a mixture of 160 parts SR-Solvent [C6H4 (CF3) 2] and 40 parts Vertrel XF (C5H2F10), and the solution was treated with a toluene solution of 0.2 part C6Oat room temperature for 20 min to give compound of C6O with III. The compound was dissolved in a mixture of 160 parts SR-Solvent and 40 parts Vertrel XF to give a precipitant-free transparent solution

ST fluorine contg calixarene prepn dispersing agent; fullerene solubilizer fluorine cong calixarene; wetting agent fluorine contg calixarene; perfluoropolyether calixarene reaction product prepn dispersant; hexachlorocyclotriphosphazene reaction product perfluoropolyether calixarene solubilizer C60

IT Metacyclophanes

RL: NUU (Other use, unclassified); RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent); USES (Uses) (calixarenes; preparation of F-containing calixarenes, compds. with carbonaceous materials, and their uses as dispersing agents, solubilizing agents, and wetting agents)

IT Nanotubes

(carbon, dispersion or solubilization of; preparation of F-containing calixarenes, compds. with carbonaceous materials, and their uses as dispersing agents, solubilizing agents, and wetting agents)

IT Fullerenes

RL: MSC (Miscellaneous)

(dispersion or solubilization of; preparation of F-containing calixarenes, compds. with carbonaceous materials, and their uses as dispersing agents, solubilizing agents, and wetting agents)

IT Carbon fibers, preparation

RL: SPN (Synthetic preparation); PREP (Preparation)

(dispersion or solubilization of; preparation of F-containing calixarenes, compds. with carbonaceous materials, and their uses as dispersing agents, solubilizing agents, and wetting agents)

IT Polyoxyalkylenes, preparation

RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)

(fluorine-containing, Fomblin Z-DOL, reaction products; preparation of F-containing calixarenes, compds. with carbonaceous materials, and their uses as dispersing agents, solubilizing agents, and wetting agents)

```
Fluoropolymers, preparation
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
         (polyoxyalkylene-, Fomblin Z-DOL, reaction products; preparation of F-containing
         calixarenes, compds. with carbonaceous materials, and their uses as
         dispersing agents, solubilizing agents, and wetting agents)
IT
     Dispersing agents
     Solubilizers
       Wetting agents
         (preparation of F-containing calixarenes, compds. with carbonaceous materials,
         and their uses as dispersing agents, solubilizing agents, and wetting
ΙT
     Inclusion compounds
     RL: SPN (Synthetic preparation); PREP (Preparation)
         (preparation of F-containing calixarenes, compds. with carbonaceous materials,
         and their uses as dispersing agents, solubilizing agents, and wetting
         agents)
ΙT
     7782-42-5, Graphite, miscellaneous
     RL: MSC (Miscellaneous)
         (dispersion or solubilization of; preparation of F-containing calixarenes,
         compds. with carbonaceous materials, and their uses as dispersing
     agents, solubilizing agents, and wetting agents) 7440-44-0, Carbon, miscellaneous
ΙT
     RL: MSC (Miscellaneous)
         (nanotubes, dispersion or solubilization of; preparation of F-containing
         calixarenes, compds. with carbonaceous materials, and their uses as
         dispersing agents, solubilizing agents, and wetting agents)
     98-17-9DP, \alpha, \alpha, \alpha-Trifluoro-m-cresol, reaction products
IT
     with calixarenes, hexachlorocyclotriphosphazene, and perfluoropolyethers
     940-71-6DP, Hexachlorocyclotriphosphazene, reaction products with
     perfluoropolyethers, calixarenes, and optionally (trifluoromethyl)phenol 68971-82-4DP, 4-tert-Butylcalix(8)arene, reaction products with
     hexachlorocyclotriphosphazene, perfluoropolyethers, and optionally (trifluoromethyl)phenol 146349-51-1DP, Demnum SA 1, reaction products
     with hexachlorocyclotriphosphazene and calixarenes 701909-00-4P,
     Krytox 157FS(L) ester with calix(8) arene
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
         (preparation of F-containing calixarenes, compds. with carbonaceous materials,
         and their uses as dispersing agents, solubilizing agents, and wetting
         agents)
IT
     99685-96-8DP, C60 Fullerene, compds. with F-containing calix(8) arene compds.
     RL: SPN (Synthetic preparation); PREP (Preparation)
         (preparation of F-containing calixarenes, compds. with carbonaceous materials,
         and their uses as dispersing agents, solubilizing agents, and wetting
         agents)
     701909-00-4P, Krytox 157FS(L) ester with calix(8) arene
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
         (preparation of F-containing calixarenes, compds. with carbonaceous materials,
         and their uses as dispersing agents, solubilizing agents, and wetting
         agents)
     701909-00-4 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl) -\omega-(heptafluoropropoxy)-, ester with nonacyclo[43.3.1.13, 7.19, 13.115, 19.121, 25.127, 31.133, 37.139, 43] hexapentaco
     nta-1 (49), 3, 5, 7 (56), 9, 11, 13 (55), 15, 17, 19 (54), 21, 23, 25 (53), 27, 29, 31 (52), 33,
     35, 37(51), 39, 41, 43(50), 45, 47-tetracosaene-49, 50, 51, 52, 53, 54, 55, 56-octol
      (9CI) (CA INDEX NAME)
     CM
     CRN
           90317-74-1
           (C3 F6 0)n C6 H F11 03
     CMF
     CCI IDS, PMS
```

$$F-CF_2-CO_2H = 0-(C_3F_6) = n = 0-(CF_2)_3-F$$

CM 2

CRN 82452-93-5 CMF C56 H48 08

L24 ANSWER 5 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:86949 HCAPLUS

DN 140:341148

ED Entered STN: 03 Feb 2004

TI Estimation of foam forming properties and surface tension of fire-extinguishing agents

AU Meissner, E.; Twardochleb, B.; Milchert, E.; Wroblewska, A.; Szymanowski,

CS Kedzierzyn-Kozle, Pol.

SO Tenside, Surfactants, Detergents (2003), 40(6), 353-360 CODEN: TSDEES; ISSN: 0932-3414

Carl Hanser Verlag

DT Journal

LA English

CC 46-4 (Surface Active Agents and Detergents)

Section cross-reference(s): 37

AB Thirty-six fire-extinguishing agents of the Aqueous Film Forming Foams (AFFF) type were prepared, and some of their properties investigated. Each of them contained at least two surfactants with a perfluoroalkyl hydrophobic chain and an anionic, cationic, nonionic or zwitterionic polar head. The synergisms in surface tension reduction and foaming properties of the fire-extinguishing agents were considered. Apart from perfluoroorg. compds. the agents also contain surfactants with a hydrocarbon hydrophobic chain, organic solvents of the "Cellosolve" type, foam stabilizers and antifreeze agents. The lowest values of surface tensions for aqueous solns. are achieved with anionic (KK, SATT, PFKA) or zwitterionic compds. (SB, CB). The foaming ability and foam stability increases with the increase in anionic surfactant concentration

ST perfluoroorg surfactant anionic surface tension fire extinguishing agent

IT Surfactants

(anionic; preparation and estimation of foam forming properties and surface tension of fire-extinguishing agents)

IT Surfactants

(cationic; preparation and estimation of foam forming properties and surface tension of fire-extinguishing agents)

IT Surfactants

(nonionic; preparation and estimation of foam forming properties and surface tension of fire-extinguishing agents)

IT Fire extinguishers

Foams

Surface tension

(preparation and estimation of foam forming properties and surface tension of fire-extinguishing agents)

```
Surfactants
         (zwitterionic; preparation and estimation of foam forming properties and surface
         tension of fire-extinguishing agents)
      15166-06-0P
                     15899-28-2P 15899-32-8P
                                                       15957-30-9P 680576-87-8P
IT
                       680576-89-0P
      680576-88-9P
                                        680576-90-3P
                                                          680576-98-1P
                                                                            680576-99-2P
      680577-00-8P
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
          (preparation and estimation of foam forming properties and surface tension of
         fire-extinguishing agents)
     60-24-2 74-88-4, reactions 75-21-8, Oxirane, reactions 75-65-0, tert-Butyl alcohol, reactions 79-11-8, Chloroacetic acid, reactions 103-76-4, 1-Piperazineethanol 107-18-6, Allyl alcohol, reactions
     108-00-9 109-89-7, Diethylamine, reactions 111-42-2, reactions 121-44-8, Triethylamine, reactions 662-27-1 677-90-7 677-93-0 678-16-0 865-77-0 1120-71-4 1310-73-2, Sodium hydroxide, reactions 1514-90-5 2355-30-8 3486-08-6 7719-09-7, Thionyl chloride
                    680576-92-5
                                     680576-93-6
      680576-91-4
      RL: RCT (Reactant); RACT (Reactant or reagent)
          (preparation and estimation of foam forming properties and surface tension of
         fire-extinguishing agents)
     15165-97-6P 152074-60-7P 680576-97-0P 680577-02-0P 680577-06-4P
IT.
      RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
      (Reactant or reagent)
          (preparation and estimation of foam forming properties and surface tension of
         fire-extinguishing agents)
                                        149270-40-6P 680576-94-7P
      149270-38-2P
                       149270-39-3P
                                                                            680576-95-8P
      680576-96-9P
     RL: SPN (Synthetic preparation); PREP (Preparation)
         (preparation and estimation of foam forming properties and surface tension of
         fire-extinguishing agents)
                       680577-01-9P
                                         680577-04-2P
     465499-94-9P
                                                           680577-05-3P
      680577-07-5P
                      680577-08-6P
                                        680577-09-7P 680577-10-0P
                                                                            680577-11-1P
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
          (surfactant; preparation and estimation of foam forming properties and surface
         tension of fire-extinguishing agents)
                THERE ARE 14 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE. CNT 14
RE
(1) Chambers, R; Prac Chem Soc 1961, P113 HCAPLUS
(2) Dams, R; WO 45167 1997 HCAPLUS
(3) Fiters, 0; Fine Technical 1969, V5, P284
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(6) Halasz, S; Ullmans Encylopadie der Technischen Chemie 1976, V11, P632
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(8) Hauptschein, M; J Am Chem Soc 1961, V83, P2495 HCAPLUS
(9) Kissa, E; Fluorinated Surfactants, Surfactant Science Series 1994, V50,
(10) Orlowski, A; Fire Precautions in Technical 1973, V1, P16 (11) Redies, F; DE 2559189 1975 HCAPLUS
(12) Ruschke, H; DE 2315326 1973 HCAPLUS
(13) Wikinson, J; Chem Rev 1992, V92, P505
(14) Wilczkowski, S; New fire extinguishing agents 1995
      465499-94-9P
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
         (surfactant; preparation and estimation of foam forming properties and surface
         tension of fire-extinguishing agents)
      465499-94-9 HCAPLUS
RN
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], \alpha-(1-carboxy-
      1, 2, 2, 2-tetrafluoroethyl)-\omega-[1, 2, 2, 2-tetrafluoro-1-
```

(trifluoromethyl)ethoxy]-, ammonium salt (9CI) (CA INDEX NAME)

```
F_3C - \begin{bmatrix} CO_2H \\ - C_1 \\ - C_2 \end{bmatrix} = \begin{bmatrix} CF_3 \\ - CF_3 \\ - CF_3 \end{bmatrix}
```

## NH3

```
ANSWER 6 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
     2003:892828 HCAPLUS
AN
DN
     139:365763
     Entered STN: 14 Nov 2003
ED
ΤI
     High vinyl ether modified sinterable polytetrafluoroethylene
     Aten, Ralph M.; Libert, Sharon Ann
E. I. Du Pont de Nemours & Co., USA
IN
PA
     PCT Int. Appl., 26 pp.
     CODEN: PIXXD2
DT
     Patent
LA
     English
IC
     ICM C08F214-26
CC
     37-3 (Plastics Manufacture and Processing)
FAN. CNT 1
                                 DATE
     PATENT NO.
                                              APPLICATION NO.
                                                                      DATE
                          KIND
     WO 2003093333
                                  20031113
                                                                      20030429
PΙ
                                              WO 2003-US13210.
                           A 1
         W: CN, JP
         RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
             IT, LU, MC, NL, PT, RO, SE, SI, SK, TR
     US 2003216531
                                 20031120
                                              US 2003-420144
                                                                      20030422
                           A1
     US 6870020
                                  20050322
                           B2
     EP 1499650
                                 20050126
                                              EP 2003-721917
                                                                      20030429
                           A1
         R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, FI, RO, CY, TR, BG, CZ, EE, HU, SK
             IE, SI, FI, RO, CY,
PRAI US 2002-376645P
                                 20020430
                           P
                           W
     WO 2003-US13210
                                  20030429
CLASS
                        PATENT FAMILY CLASSIFICATION CODES
PATENT NO.
                 CLASS
 WO 2003093333
                 ICM
                         C08F214-26
 WO 2003093333
                 ECLA
                         C08F214/26D
                         526/247.000; 526/250.000
US 2003216531
                 NCL
                         C08F214/26D
                 ECLA
     Disclosed is a modified polytetrafluoroethylene powder of a sinterable
     copolymer of tetrafluoroethylene containing .apprx. 0.5-10% of fluorinated
     vinyl ether, the copolymer having a melt creep viscosity of greater than
     about 1 x 106 Pa S. In preferred embodiments, the sinterable
     copolymer has a melt creep viscosity of greater than .apprx.1 x 107
     Pa·S and fluorinated vinyl ether content of from .apprx. 1-7%. The
     polymer has a combination of a high level of fluorinated vinyl ether and a
     melt creep viscosity which is high enough to enable the fabrication of
     articles by sintering.
     sinterable vinyl ether modified polytetrafluoroethylene powder melt creep
     viscosity
     Fluoropolymers, preparation
     RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or
     engineered material use); PREP (Preparation); USES (Uses)
        (manufacture of high vinyl ether modified sinterable polytetrafluoroethylene
        with high melt creep viscosity)
     Surfactants
        (non-telogenic fluorinated compound; in manufacture of high vinyl ether
        modified sinterable polytetrafluoroethylene with high melt creep
        viscosity)
ΙT
     Polyethers, uses
     RL: MOA (Modifier or additive use); USES (Uses)
        (perfluoro, carboxy-containing, for surfactants; in manufacture of high vinyl
        ether modified sinterable polytetrafluoroethylene with high melt creep
```

```
viscosity)
     Fluoropolymers, uses
     RL: MOA (Modifier or additive use); USES (Uses)
         (polyether-, perfluoro, carboxy-containing, for surfactants; in manufacture of
        high vinyl ether modified sinterable polytetrafluoroethylene with high
        melt creep viscosity)
     26425-79-6P, Perfluoro (methyl vinyl ether)-tetrafluoroethylene copolymer
IT
     26655-00-5P, Perfluoro (propyl vinyl ether)-tetrafluoroethylene copolymer
     31784-04-0P, Perfluoro (ethyl vinyl ether)-tetrafluoroethylene copolymer
     RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
         (manufacture of high vinyl ether modified sinterable polytetrafluoroethylene
     with high melt creep viscosity)
90317-74-1, KRYTOX 157FSL 196623-59-3, Fluorolink C
IT
     RL: MOA (Modifier or additive use); USES (Uses)
         (surfactants; in manufacture of high vinyl ether modified sinterable
        polytetrafluoroethylene with high melt creep viscosity)
RE. CNT
               THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Daikin Ind Ltd; EP 0583481 A 1994 HCAPLUS
(2) Fasig, E; US 3819594 A 1974 HCAPLUS
(3) Franklin, G; US 3635926 A 1972
(4) Khan, A; US 4380618 A 1983 HCAPLUS
(5) Nakamura, Y; US 5709944 A 1998
     90317-74-1, KRYTOX 157FSL
     RL: MOA (Modifier or additive use); USES (Uses)
         (surfactants; in manufacture of high vinyl ether modified sinterable
        polytetrafluoroethylene with high melt creep viscosity)
     90317-74-1 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
CN
     1, 2, 2, 2-tetrafluoroethyl)-\o-(heptafluoropropoxy)- (9CI) (CA INDEX
         0-(C_3F_6) n 0-(CF_2)_3-F
```

```
L24 ANSWER 7 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
     2003:541285 HCAPLUS
AN
     139:231047
     Entered STN: 16 Jul 2003
ED
     Dispersion Polymerizations of Methyl Methacrylate in Supercritical Carbon
     Dioxide-with a Novel Ester End-Capped Perfluoropolyether Stabilizer
     Wang, Wenxin; Naylor, Andrew; Howdle, Steven M.
School of Chemistry, University of Nottingham, Nottingham, NG7 2RD, UK
Macromolecules (2003), 36(14), 5424-5427
CODEN: MAMOBX; ISSN: 0024-9297
CS
S<sub>0</sub>
     American Chemical Society
DT
     Journal
     English
     35-4 (Chemistry of Synthetic High Polymers)
     Dispersion polymerization of Me methacrylate in supercrit. CO2 was performed in
     the presence of a well-defined ester end-capped perfluoropolyether (I),
     which was prepared by reaction of acid-terminated perfluoropolyether with
     butanol. I acted as a dispersion agent, keeping the growing polymer
     chains dispersed in the reaction medium.
ST
     perfluoropolyether dispersing agent methacrylate polymn supercrit carbon
     dioxide
     Dispersing agents
     Polymerization
         (dispersion polymerization of Me methacrylate in supercrit. carbon dioxide
         with perfluoropolyether dispersing agent)
IT
     Polyoxyalkylenes, uses
     RL: NUU (Other use, unclassified); USES (Uses)
         (fluorine-containing; dispersion polymerization of Me methacrylate in supercrit.
```

carbon dioxide with perfluoropolyether dispersing agent)

```
Fluoropolymers, uses
      RL: NUU (Other use, unclassified); USES (Uses)
          (polyoxyalkylene-; dispersion polymerization of Me methacrylate in supercrit.
          carbon dioxide with perfluoropolyether dispersing agent)
      124-38-9, Carbon dioxide, uses
      RL: NUU (Other use, unclassified); USES (Uses)
          (dispersion polymerization of Me methacrylate in supercrit. carbon dioxide
          with perfluoropolyether dispersing agent)
     146166-99-6P, Krytox 157FSL butyl ester
RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
          (dispersion polymerization of Me methacrylate in supercrit. carbon dioxide
          with perfluoropolyether dispersing agent)
      9011-14-7P, Methyl methacrylate homopolymer
      RL: SPN (Synthetic preparation); PREP (Preparation)
          (dispersion polymerization of Me methacrylate in supercrit. carbon dioxide
          with perfluoropolyether dispersing agent)
RE. CNT 19
                 THERE ARE 19 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
    Canelas, D; Macromolecules 1997, V30, P5673 HCAPLUS
    Christian, P; Macromolecules 2000, V33, P237 HCAPLUS Christian, P; Macromolecules 2000, V33, P9222 HCAPLUS
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(9) Howdle, S; Chemical Synthesis Using Supercritical Fluids 1999, P147 HCAPLUS
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(11) Jessop, P; Chemical Synthesis Using Supercritical Fluids 1999
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(19) Yong, T; Chem Commun 1997, P1811 HCAPLUS
     146166-99-6P, Krytox 157FSL butyl ester
RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
          (dispersion polymerization of Me methacrylate in supercrit. carbon dioxide
          with perfluoropolyether dispersing agent)
      146166-99-6 HCAPLUS
      Poly[oxy[trif]uoro(trif]uoromethyl)-1, 2-ethanediyl]], \alpha-[1-(butoxycarbonyl)-1, 2, 2, 2-tetraf]uoroethyl]-\alpha-(heptaf]uoropropoxy)-
       (9CI) (CA INDEX NAME)
ANSWER 8 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
      2003:434953 HCAPLUS
AN
DN
      139:11320
      Entered STN: 06 Jun 2003
      Method and apparatus for decontamination of sensitive equipment
ΤI
      Kaiser, Robert
IN
PA
      USA
      U.S. Pat. Appl. Publ., 40 pp.
      CODEN: USXXCO
DT
      Patent
LA
      English
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ICM B08B003-12

INCL 134001000; 134010000; 134018000

```
59-6 (Air Pollution and Industrial Hygiene)
FAN. CNT 1
     PATENT NO.
                                                                    DATE
                         KIND
                                            APPLICATION NO.
                                DATE
                                                                    20020523
                                20030605
                                            US 2002-154488
     US 2003102007
                          A1
PRAI US 2001-292967P
                                20010523
CLASS
PATENT NO.
                 CLASS
                        PATENT FAMILY CLASSIFICATION CODES
 US 2003102007
                 ICM
                        B08B003-12
                 INCL
                        134001000; 134010000; 134018000
 US 2003102007
                 NCL
                        134/001.000; 134/010.000; 134/018.000
                 ECLA
                        B08B003/02; B08B003/12
     Ultrasonic solvent cleaning processes can effectively decontaminate
     sensitive electronic and optical equipment exposed to chemical or biol.
     warfare agents. Contaminant removal occurs in three steps: removal of the
     contaminant from the surface of the part being processed, transfer of the
     dissolved or suspended contaminant into the bulk of the decontamination
     liquid in the immersion sump, and then removal of the dissolved contaminant
     by activated carbon adsorption, or suspended contaminant by filtration.
     When agent contaminated decontamination liquid is passed through a bed of
     activated carbon, the agent adsorbs onto the activated carbon, resulting
     in agent free decontamination liquid that can be recycled and reused. The
     method is nonflammable, nontoxic, and environmentally acceptable.
     Ultrasonic agitation provides effective mass and phys. transfer of
     contaminants from the surfaces of the objects being decontaminated to the
     bulk of the decontamination liquid Decontamination of sensitive equipment
     in decontamination fluid can be performed in com. available ultrasonic
     vapor degreasers.
ST
     chem warfare agent removal electronic app ultrasonic solvent cleaning;
     biol warfare agent removal electronic app ultrasonic solvent cleaning
IT
     Surfactants
        (fluorinated; method and apparatus for decontamination of sensitive
        equipment)
IT
     Hydrocarbons, uses
     RL: NUU (Other use, unclassified); USES (Uses)
        (fluoro; method and apparatus for decontamination of sensitive equipment)
IT
     Biological warfare agents
     Chemical warfare agents
     Sound and Ultrasound
        (method and apparatus for decontamination of sensitive equipment)
     7440-44-0, Carbon, uses
     RL: NUU (Other use, unclassified); USES (Uses)
        (activated; method and apparatus for decontamination of sensitive equipment)
     335-76-2, Perfluorodecanoic Acid 25038-02-2, Krytox Alcohol
     51798-33-5, Krytox 157FS(H) 90317-74-1, Krytox 157FS(L)
     106441-39-8, Fomblin Z Diacid 163702-05-4, HFE 7200
                                                             219484-64-7, HFE
     7100 533902-85-1, HFE 7500
     RL: NUU (Other use, unclassified); USES (Uses)
        (method and apparatus for decontamination of sensitive equipment)
```

112-80-1, Oleic acid, uses 143-28-2, Oleyl alcohol 532993-09-2,
Rhodasurf LA 3 532993-30-9, Rhodasurf LAN 3
RL: MOA (Modifier or additive use); USES (Uses)
 (surfactant; method and apparatus for decontamination of sensitive equipment)
90317-74-1, Krytox 157FS(L)
RL: NUU (Other use, unclassified); USES (Uses)
 (method and apparatus for decontamination of sensitive equipment)

RN 90317-74-1 HCAPLUS
CN Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX
NAME)

$$F-CF_2 CO_2H$$
 $O-(C_3F_6)$ 
 $O-(CF_2)_3-F$ 

IT

```
ANSWER 9 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
L24
     2003:4622 HCAPLUS
DN
     139:370139
     Entered STN: 03 Jan 2003
     Interfacial studies of the formation of microemulsions of water in carbon
     dioxide with fluorinated surfactants. [Erratum to document cited in
     CA137:2068261
AU
     Psathas, Petros A.; Sander, Edward A.; Ryoo, Won; Mitchell, Daniel;
     Felling, Kyle W.; Lagow, Richard J.; Lim, Kwon Tae; Johnston, Keith P. Department of Chemical Engineering, The University of Texas at Austin,
CS
     Austin, TX, 78712, USA
     Journal of Dispersion Science and Technology (2002), 23(6), b853
S<sub>0</sub>
     CODEN: JDTEDS; ISSN: 0193-2691
Marcel Dekker, Inc.
PR
     Journal
DT
LA
     English
CC
     66-2 (Surface Chemistry and Colloids)
     Section cross-reference(s): 35
     The name of Kyle W. Felling is added to the by-line as the fifth author.
ST
     erratum interfacial tension microemulsion water carbon dioxide fluorinated
     surfactant; salinity microemulsion water carbon dioxide light scattering
     erratum
     Polyoxyalkylenes, preparation
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
        (fluorine-containing, surfactants; interfacial studies of formation of
        microemulsions of water in carbon dioxide with fluorinated surfactants
        as function of (Erratum))
IT
     Interfacial tension
        (interfacial studies of formation of microemulsions of water in carbon
        dioxide with fluorinated surfactants (Erratum))
IT
     Salinity
         (interfacial studies of formation of microemulsions of water in carbon
        dioxide with fluorinated surfactants as function of (Erratum))
ΙT
     Surfactants
        (ionic; interfacial studies of formation of microemulsions of water in
        carbon dioxide with fluorinated surfactants (Erratum))
     Emulsions
         (microemulsions; interfacial studies of formation of microemulsions of
        water in carbon dioxide with fluorinated surfactants (Erratum))
IT
     Fluoropolymers, preparation
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP
     (Preparation); USES (Uses)
        (polyoxyalkylene-, surfactants; interfacial studies of formation of microemulsions of water in carbon dioxide with fluorinated surfactants
        as function of (Erratum))
     Polyoxyalkylenes, reactions
     Polyoxyalkylenes, reactions
     RL: RCT (Reactant); RACT (Reactant or reagent)
        (preparation of perfluoro Me ether poly(ethylene glycol) carboxylic acids as
        surfactants for microemulsions of water in carbon dioxide (Erratum))
IT
     454221-32-0
     RL: NUU (Other use, unclassified); USES (Uses)
        (interfacial studies of formation of microemulsions of water in carbon
        dioxide with fluorinated surfactants (Erratum))
     124-38-9, Carbon dioxide, properties 7732-18-5, Water, properties
     RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
        (interfacial studies of formation of microemulsions of water in carbon
        dioxide with fluorinated surfactants (Erratum))
     454170-74-2P
IT
                    454170-75-3P
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
        (preparation of perfluoro Me ether poly(ethylene glycol) carboxylic acids as
        surfactants for microemulsions of water in carbon dioxide (Erratum))
     76-13-1, 1, 1, 2-Trichlorotrifluoroethane 9004-74-4, Poly(ethylene glycol)
     methyl ether 25322-68-3, Poly(ethylene glycol)
RL: RCT (Reactant); RACT (Reactant or reagent)
        (preparation of perfluoro Me ether poly(ethylene glycol) carboxylic acids as
```

Et 
$$CH_2$$
) 3-0- $C$   $CH_2$ ) 3-0- $C$   $CH_2$ ) 3-0- $C$   $CH_2$ ) 3-F

C1<sup>−</sup>

ANSWER 10 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN L24 2002:471751 HCAPLUS 137:206826 DN Entered STN: 24 Jun 2002 Interfacial studies of the formation of microemulsions of water in carbon dioxide with fluorinated surfactants Psathas, Petros A.; Sander, Edward A.; Ryoo, Won; Mitchell, Daniel; Lagow, AU Richard J.; Lim, Kwon Taek; Johnston, Keith P. Department of Chemical Engineering, The University of Texas at Austin, Austin, TX, 78712, USA
Journal of Dispersion Science and Technology (2002), 23(1-3), 81-92 CS S0 CODEN: JDTEDS; ISSN: 0193-2691 PB Marcel Dekker, Inc. DT Journal English LA 66-2 (Surface Chemistry and Colloids) CC Section cross-reference(s): 35 Measurements of the interfacial tension, y, for water-CO2-

Measurements of the interfacial tension, γ, for water-CO2perfluoropolyether (PFPE) ionic surfactant systems are utilized to
understand the surfactant affinity for the various phases and adsorption
at the interface. A marked decrease in γ with salinity is observed as
salt screens electrostatic repulsion and induces microemulsion formation,
as confirmed with dynamic light scattering. In several cases, the
interfacial tension goes through an unusual maximum with salinity, which is
explained in terms of competition between surfactant affinity for the
various phases and microemulsion formation. Fundamental studies of
interfacial properties provide important insight for designing surfactants
and exptl. conditions to achieve the desired properties of water/CO2
microemulsions and emulsions.

ST interfacial tension microemulsion water carbon dioxide fluorinated surfactant; salinity microemulsion water carbon dioxide light scattering

T Polyoxyalkylenes, preparation RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)

(fluorine-containing, surfactants; interfacial studies of formation of microemulsions of water in carbon dioxide with fluorinated surfactants as function of)

IT Interfacial tension

(interfacial studies of formation of microemulsions of water in carbon dioxide with fluorinated surfactants)

IT Salinity

(interfacial studies of formation of microemulsions of water in carbon dioxide with fluorinated surfactants as function of)

IT Surfactants

(ionic; interfacial studies of formation of microemulsions of water in carbon dioxide with fluorinated surfactants)

```
Emulsions
           (microemulsions; interfacial studies of formation of microemulsions of
          water in carbon dioxide with fluorinated surfactants)
IT
      Fluoropolymers, preparation
      RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
          (polyoxyalkylene-, surfactants; interfacial studies of formation of microemulsions of water in carbon dioxide with fluorinated surfactants
          as function of)
      Polyoxyalkylenes, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
IΤ
           (preparation of perfluoro Me ether poly(ethylene glycol) carboxylic acids as
          surfactants for microemulsions of water in carbon dioxide)
IT
      454221-32-0
      RL: NUU (Other use, unclassified); USES (Uses)
          (interfacial studies of formation of microemulsions of water in carbon
          dioxide with fluorinated surfactants)
      124-38-9, Carbon dioxide, properties 7732-18-5, Water, properties RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
           (interfacial studies of formation of microemulsions of water in carbon
          dioxide with fluorinated surfactants)
      454170-74-2P 454170-75-3P
IΤ
      RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
           (preparation of perfluoro Me ether poly(ethylene glycol) carboxylic acids as
          surfactants for microemulsions of water in carbon dioxide)
      76-13-1, 1, 1, 2-Trichlorotrifluoroethane
                                                           9004-74-4, Poly(ethylene glycol)
      methyl ether 25322-68-3, Poly(ethylene glycol)
RL: RCT (Reactant); RACT (Reactant or reagent)
          (preparation of perfluoro Me ether poly(ethylene glycol) carboxylic acids as
          surfactants for microemulsions of water in carbon dioxide)
                 THERE ARE 69 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE. CNT
RE
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                                                              V33, P183 HCAPLUS
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     HCAPLUS
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- **HCAPLUS** (55) Psathas, P; J Disp Sci Tech 2002, V33, P81 (56) Ruckenstein, E; Advances in Colloid and Interface Science 1999, V79, P59
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- 454221-32-0
  - RL: NUU (Other use, unclassified); USES (Uses) (interfacial studies of formation of microemulsions of water in carbon dioxide with fluorinated surfactants)
- 454221-32-0 HCAPLUS
- CN Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]],  $\alpha$ -[1-[[3-(diethylmethylammonio)propoxy]carbonyl]-1, 2, 2, 2-tetrafluoroethyl]-w-(heptafluoropropoxy)-, chloride (9CI) (CA INDEX NAME)

Et 
$$0$$
  
Et  $N^+$  (CH2) 3  $-$  0  $-$  C  
Me  $F-CF_2 0-$  (C3F6)  $n$  0  $-$  (CF2) 3  $-$  F

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L24 ANSWER 11 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
     2002:471750 HCAPLUS
AN
DN
     137:206825
     Entered STN: 24 Jun 2002
ED
     Mapping the stability and curvature of emulsions of H2O and supercritical
     CO2 with interfacial tension measurements
    Psathas, Petros A.; Sander, Edward A.; Lee, Min Young; Lim, Kwon Taek;
     Johnston, Keith P.
CS
    Department of Chemical Engineering, The University of Texas at Austin,
    Austin, TX, 78712, USA
Journal of Dispersion Science and Technology (2002), 23(1-3), 65-80
S0
     CODEN: JDTEDS; ISSN: 0193-2691
PR
     Marcel Dekker, Inc.
DT
     Tournal
     English
CC
     66-2 (Surface Chemistry and Colloids)
     Section cross-reference(s): 35
     The stability and curvature of emulsions of H2O and CO2 are reported and
     analyzed in terms of measurements of interfacial tension vs. formulation
     variables, including salinity, CO2 d., temperature and pH. Among the
    surfactants studied are, quaternary ammonium cationic ones with perfluoropolyether tails, block copolymer ionomers and a poly(hydroxyethyl
     methacrylate) with polydimethylsiloxane tails, and a nonionic ethylene
     oxide surfactant with a fluoroalkane tail. The interfacial tension
     measurements were made at surfactant concns. from 0.05 to 1.0 weight% with a
     variable-volume pendant drop tensiometer up to 345 bar and 363° K. As
     a formulation variable was varied, the system reached a balanced state
     characterized by a min. in interfacial tension, a loss in emulsion
     stability and in some cases an inversion from a W/C to C/W emulsion.
     the Marangoni-Gibbs stabilization weakens, and also it becomes easy to
     bend and rupture the surfactant monolayer, causing coalescence. Except in
     the case of the nonionic fluorinated surfactant C8F17-S02NEt-(CH2CH2O)12-
     14CH3, the crossover from the CO2-continuous (W/C) to the H2O-continuous
     (C/W) emulsion occurred abruptly due to clouding of the surfactant out of
     the CO2 phase. For PFPE-TMAA, the plot of \gamma vs. surfactant concentration
     revealed both pre-micellar aggregates and a critical microemulsion, each of
     which was dependent on salinity.
ST
     emulsion water supercrit carbon dioxide stability curvature interfacial
     tension; surfactant water supercrit carbon dioxide emulsion stability
     curvature
    Polysiloxanes, preparation
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP
     (Preparation); USES (Uses)
        (acrylic, block; mapping stability and curvature of emulsions of H20
        and supercrit. CO2 with interfacial tension measurements)
IT
     Surfactants
        (cationic; mapping stability and curvature of emulsions of H2O and
        supercrit. CO2 with various surfactants)
    Polyoxyalkylenes, preparation
     RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP
     (Preparation); USES (Uses)
        (fluorine-containing, cationic surfactants; mapping stability and curvature
        of emulsions of H2O and supercrit. CO2 with interfacial tension
        measurements)
ΙT
    Surfactants
        (ionomer; mapping stability and curvature of emulsions of H2O and
        supercrit. CO2 with various surfactants)
ΙT
     Interfacial tension
        (mapping stability and curvature of emulsions of H2O and supercrit. CO2
        with interfacial tension measurements)
IT
     Coalescence
     Monolayers
     Stability
        (mapping stability and curvature of emulsions of H2O and supercrit. CO2
        with various surfactants)
ΙT
    Emulsions
        (microemulsions; mapping stability and curvature of emulsions of H20
        and supercrit. CO2 with various surfactants)
IT
        (nonionic; mapping stability and curvature of emulsions of H2O and
```

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supercrit. CO2 with various surfactants)
 IT
        Fluoropolymers, preparation
        RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
             (polyoxyalkylene-, cationic surfactants; mapping stability and
            curvature of emulsions of H2O and supercrit. CO2 with interfacial
            tension measurements)
        124-38-9, Carbon dioxide, properties 7732-18-5, Water, properties
        RL: PRP (Properties)
             (mapping stability and curvature of emulsions of H2O and supercrit. CO2
            with interfacial tension measurements)
        1652-63-7, FC-135 29117-08-6, FC-170C
                                                                    227018-51-1D, hydrolyzed
        287735-36-8D, hydrolyzed 393855-40-8D, hydrolyzed 454221-30-8
        RL: NUU (Other use, unclassified); USES (Uses)
             (mapping stability and curvature of emulsions of H2O and supercrit. CO2
            with various surfactants)
 IT
        454221-29-5P
        RL: NUU (Other use, unclassified); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
             (mapping stability and curvature of emulsions of H2O and supercrit. CO2
            with various surfactants)
        616-39-7, N, N-Diethylmethylamine 90317-74-1
        RL: RCT (Reactant); RACT (Reactant or reagent)
             (preparation of cationic perflurorpolyether surfactant for use in emulsions
            of H2O and supercrit. CO2)
        454221-28-4P
        RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
        (Reactant or reagent)
            (preparation of cationic perflurorpolyether surfactant for use in emulsions
            of H20 and supercrit. CO2)
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- 454221-30-8
  - RL: NUU (Other use, unclassified); USES (Uses)
    - (mapping stability and curvature of emulsions of H2O and supercrit. CO2 with various surfactants)
- 454221-30-8 HCAPLUS
- Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]],  $\alpha$ -[1-[[[[(carboxymethyl)dimethylammonio]methyl]amino]carbonyl]-1, 2, 2, 2tetrafluoroethyl]-ω-(heptafluoropropoxy)-, inner salt (9CI) (CA INDEX NAME)

$$\begin{array}{c} -02 \text{C} - \text{CH}_2 - \stackrel{\text{Me}}{\stackrel{\text{V}^+}{\stackrel{\text{C}}{\rightarrow}}} \text{CH}_2 - \text{NH} - \stackrel{\text{C}^-}{\text{C}^-} \stackrel{\text{C}^-}{\stackrel{\text{C}^-}{\stackrel{\text{C}^-}{\rightarrow}}} 0 - \text{(C3F6)} - \stackrel{\text{I}^-}{\stackrel{\text{D}^-}{\rightarrow}} 0 - \text{CF}_2 - \text{CF}_2 - \text{CF}_3 \end{array}$$

- RL: RCT (Reactant); RACT (Reactant or reagent)
- (preparation of cationic perflurorpolyether surfactant for use in emulsions of H2O and supercrit. CO2) 90317-74-1 HCAPLUS
- Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]],  $\alpha$ -(1-carboxy-1, 2, 2, 2-tetrafluoroethyl)-@-(heptafluoropropoxy)- (9CI) (CA INDEX

$$F-CF_2-CO_2H \longrightarrow O-(C_3F_6) \longrightarrow O-(CF_2)_3-F$$

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454221-28-4P
IΤ
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RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(preparation of cationic perflurorpolyether surfactant for use in emulsions of H2O and supercrit. CO2)

454221-28-4 HCAPLUS

CN Poly[oxy[trif]uoro(trif]uoromethyl)-1, 2-ethanediyl]],  $\alpha$ -[1-[(3chloropropoxy)carbonyl]-1, 2, 2, 2-tetrafluoroethyl]-\omega-(heptafluoropropoxy)- (9CI) (CA INDEX NAME)

$$\text{C1- (CH2)}_{\,3} - 0 - \text{C-} \underbrace{\text{CF3}}_{F} - 0 - (\text{C3F6}) - \underbrace{\frac{1}{n}}_{n} 0 - \text{CF2} - \text{CF2} - \text{CF3}$$

ANSWER 12 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN L24

2002:403912 HCAPLUS

DN 136:402218

ED Entered STN: 30 May 2002

Aqueous dispersion polymerization of fluoromonomers using fluorosurfactant ΤI

IN Morgan, Richard Alan; Jones, Clay Woodward; Treat, Theodore; Hrivnak, Jeffrey A.

E. I. Du Pont de Nemours & Co., USA PA

U.S., 15 pp., Cont.-in-part of U.S. Ser. No. 570,853. CODEN: USXXAM

DT Patent

English

IC ICM C08F014-18

INCL 526214000

35-4 (Chemistry of Synthetic High Polymers)

FAN. CNT 2	Stry Or	Synthe	cic night for	/mers/			
PATENT NO.		KIND	DATE	APPLICATION NO.	DATE		
PI US 6395848 US 6429258 PRAI US 1999-135 US 2000-570		B1 B1 P A2	20020528 20020806 19990520 20000512	US 2000-704333 US 2000-570853	20001102 20000512		
CLASS PATENT NO.	CLASS	PATENT	FAMILY CLASS	SIFICATION CODES			
US 6395848	US 6395848 ICM INCL		4-18 000				
US 6395848	NCL	526/209	9.000; 526/25	03.000; 524/316.000; 50.000; 526/253.000; 10.000; 526/911.000			
US 6429258	ECLA NCL	524/80 526/24	2. 000	14.000; 524/545.000;	524/546.000;		
	ECLA	C08F01	4/26+2/16; CO	08F214/26D			

 $\label{thm:continuous} \textbf{Title process comprising polymerizing at least one fluorinated monomer in an } \\$ aqueous medium containing initiator and dispersing agent to obtain an aqueous dispersion of particles of fluoropolymer, wherein said dispersing agent is a combination of at least two fluorosurfactants, at least one of said fluorosurfactants being perfluoropolyether carboxylic or sulfonic acid or salt thereof, and at least one of said fluorosurfactants being fluoroalkyl carboxylic or sulfonic acid or salt thereof, or fluoroalkoxy aryl sulfonic acid or salt thereof. Thus, hexafluoropropylene was copolymd. with tetrafluoroethylene in water containing Zonyl FS62 and Krytox 157FSL in the

presence of ammonium persulfate. aq dispersion polymn fluoromonomer fluorosurfactant perfluoropolyether

Dispersing agents

Polymerization catalysts (aqueous dispersion polymerization of fluoromonomers using fluorosurfactant)

Fluoropolymers, preparation

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

```
(aqueous dispersion polymerization of fluoromonomers using fluorosurfactant)
     Polymerization
IT
         (dispersion; aqueous dispersion polymerization of fluoromonomers using
        fluorosurfactant)
IT
     Surfactants
         (fluorosurfactants; aqueous dispersion polymerization of fluoromonomers using
        fluorosurfactant)
IT
     Polyethers, uses
     RL: MOA (Modifier or additive use); USES (Uses)
         (perfluoro, fluorosurfactant; aqueous dispersion polymerization of fluoromonomers
        using fluorosurfactant)
IT
     Fluoropolymers, uses
     RL: MOA (Modifier or additive use); USES (Uses)
         (polyether-, perfluoro, fluorosurfactant; aqueous dispersion polymerization of
        fluoromonomers using fluorosurfactant)
     9002-84-0P, Tetrafluoroethylene homopolymer
                                                       25067-11-2P.
IT
                                                             26655-00-5P, Perfluoro
     Hexafluoropropylene-tetrafluoroethylene copolymer
     propyl vinyl ether-tetrafluoroethylene copolymer
                                                             63654-40-0P,
     Hexafluoropropylene-perfluoro ethyl vinyl ether-tetrafluoroethylene
                  82606-24-4P, Perfluorobutylethylene-tetrafluoroethylene
     copolymer
                  165178-32-5P, Perfluoro methyl vinyl ether-perfluoro propyl
     copolymer
     vinyl ether-tetrafluoroethylene copolymer
     RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or
     engineered material use); PREP (Preparation); USES (Uses)
         (aqueous dispersion polymerization of fluoromonomers using fluorosurfactant)
     3825-26-1, Ammonium perfluorooctanoate 51798-33-5, Krytox 157FSH 90317-74-1, Krytox 157FS(L) 111019-20-6, Zonyl TBS
                               196623-59-3, Fluorolink C.
     120895-92-3, Demnum SH
                                                                314057-01-7, Zonyl
                            431048-66-7
     FS 62
              430474-48-9
     RL: MOA (Modifier or additive use); USES (Uses)
        (fluorosurfactant; aqueous dispersion polymerization of fluoromonomers using
        fluorosurfactant)
IT
     7727-21-1, Potassium persulfate 7727-54-0, Ammonium persulfate
     RL: CAT (Catalyst use); USES (Uses)
         (polymerization initiator; aqueous dispersion polymerization of fluoromonomers using
        fluorosurfactant)
RE. CNT
               THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
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(3) Anon; WO 9622313 1996 HCAPLUS
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(13) Seguchi; J Polym Sci Polymer Phys Ed 1974, V12, P2567 HCAPLUS
     90317-74-1, Krytox 157FS(L)
     RL: MOA (Modifier or additive use); USES (Uses)
         (fluorosurfactant; aqueous dispersion polymerization of fluoromonomers using
        fluorosurfactant)
     90317-74-1 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-\o-(heptafluoropropoxy)- (9CI) (CA INDEX
F-CF_2-\begin{bmatrix} - & & & \\ & & & \\ & & & \end{bmatrix} 0- (CF<sub>2</sub>)<sub>3</sub>-F
```

L24 ANSWER 13 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN AN 2002:61747 HCAPLUS

```
136:103982
     Entered STN: 23 Jan 2002
ED
ΤI
     Water-repellent coating compositions and production methods therefor and
     water-repellent coatings therewith for ink jet heads
     Hirano, Tadashi
IN
     Konica Co., Japan
Jpn. Kokai Tokkyo Koho, 5 pp.
PA
S0
     CODEN: JKXXAF
DT
     Patent
LA
     Tapanese
     ICM C09D201-04
IC
     ICS B41J002-135
CC
     42-10 (Coatings, Inks, and Related Products)
     Section cross-reference(s): 74
FAN. CNT 1
     PATENT NO.
                          KIND
                                  DATE
                                              APPLICATION NO.
                                                                       DATE
     JP 2002020697
                           A2
                                  20020123
                                              JP 2000-204867
                                                                       20000706
PRAI JP 2000-204867
                                  20000706
CLASS
                         PATENT FAMILY CLASSIFICATION CODES
PATENT NO.
                 CLASS
                         C09D201-04
 IP 2002020697
                 ICM
                  ICS
                         B41J002-135
     Coating compns. contain perfluorocyclopolymers, H-bonding solvent
AB
     dispersants, and polymeric dispersants. Thus, 30 g CTL 109S 30, 100 g CT solv 100 , and 2 mL Krytox 157 FSL were mixed, mixed with 20 \mu L 0scal
     1432 and 1 mL TSL 8233 to give a colloidal solution, and coated.
     water repellent coating ink jet head; perfluorocyclopolymers
     Polymers, uses
     RL: POF (Polymer in formulation); TEM (Technical or engineered material
     use); USES (Uses)
        (cyclic; water-repellent coatings for ink jet heads)
IΤ
     Fluoropolymers, uses
     RL: POF (Polymer in formulation); TEM (Technical or engineered material
     use); USES (Uses)
        (cyclo; water-repellent coatings for ink jet heads)
ΙT
        (jet-printing; water-repellent coatings for ink jet heads)
     Polyethers, uses
IT
     RL: MOA (Modifier or additive use); USES (Uses)
         (perfluoro; water-repellent coatings for ink jet heads)
IT
     Fluoropolymers, uses
     RL: MOA (Modifier or additive use); USES (Uses)
         (polyether-, perfluoro; water-repellent coatings for ink jet heads)
IT
     Colloids
       Dispersing agents
     Printing apparatus
        (water-repellent coatings for ink jet heads)
IT
     Coating materials
        (water-resistant; water-repellent coatings for ink jet heads)
     83048-65-1, TSL 8233
IT
     RL: MOA (Modifier or additive use); USES (Uses)
        (TSL 8233; water-repellent coatings for ink jet heads)
     7631-86-9, Oscal 1432, uses
     RL: MOA (Modifier or additive use); USES (Uses)
        (colloidal, Oscal 1432; water-repellent coatings for ink jet heads)
                                 13463-67-7, Titania, uses
ΙT
     1344-28-1, Alumina, uses
     RL: MOA (Modifier or additive use); USES (Uses)
         (sols; water-repellent coatings for ink jet heads)
IT
     90317-74-1, Krytox 157FS(L)
     RL: MOA (Modifier or additive use); USES (Uses)
         (water-repellent coatings for ink jet heads)
ΙT
     157710-30-0, CT solv 100
     RL: NUU (Other use, unclassified); USES (Uses)
        (water-repellent coatings for ink jet heads)
     389136-64-5, Cytop CTL 109S
ΙT
     RL: POF (Polymer in formulation); TEM (Technical or engineered material
     use); USES (Uses)
```

```
(water-repellent coatings for ink jet heads)
    90317-74-1, Krytox 157FS(L)
IT
     RL: MOA (Modifier or additive use); USES (Uses)
         (water-repellent coatings for ink jet heads)
     90317-74-1 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-\overline{\text{(heptafluoropropoxy)- (9CI)}} (CA INDEX
```

$$F-CF_2-CO_2H$$
 0-  $(C_3F_6)$  0-  $(CF_2)_3-F$ 

```
ANSWER 14 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
L24
     2000:870309 HCAPLUS
     134:229601
DN
     Entered STN: 13 Dec 2000
ED
     Supercritical drying for water-rinsed resist systems
ΤI
AU
     Namatsu, Hideo
CS
     NTT Basic Research Laboratories, Atsugi-shi, Kanagawa, 243-0198, Japan
S0
     Journal of Vacuum Science & Technology, B: Microelectronics and Nanometer
     Structures (2000), 18(6), 3308-3312
CODEN: JVTBD9; ISSN: 0734-211X
     American Institute of Physics
     Journal
DT
     English
LA
CC
     74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other
```

Reprographic Processes)

AR 2 Methods of supercrit. resist drying (SRD) using CO2 were developed for H2O-rinsed resist patterns. The key to their effectiveness is the use of a surfactant. In indirect SRD, a solution of n-hexane, a CO2-philic liquid, and a surfactant, sorbitan fatty acid ether, 1st replaces the H2O, and is in turn replaced with liquid CO2 before SRD is performed. The addition of a compound with a high hydrophilic-lipophilic balance to the surfactant compensates for the poor miscibility of H2O in a solution of n-hexane and sorbitan fatty acid ether. In direct SRD, which does not require a CO2-philic liquid, the H2O is replaced directly with liquid CO2 containing a surfactant, fluoroether carboxylate, which makes H20 miscible in CO2; and then SRD is performed. The excellent results obtained by both methods demonstrate that there is no inherent barrier to the use of SRD on H20-rinsed resist patterns.

ST supercrit drying water rinse resist system surfactant carbon dioxide; fluoroether carboxylate sorbitan ethylene glycol laurate oleate resist drying

IT Resists

RE

## Surfactants

(direct and indirect methods of supercrit, resist drying using surfactant to replace rinse water with liquid carbon dioxide)

IT (supercrit.; direct and indirect methods of supercrit. resist drying using surfactant to replace rinse water with liquid carbon dioxide) 1338-39-2, Span 20 7732-18-5, Water, processes 9005-64-5, Polyoxyethylene sorbitan monolaurate 7732-18-5, Water, processes 8007-43-0, Arlacel 83 IT 9005-70-3, 26266-58-0, Span 85 Polyoxyethylene sorbitan trioleate 26027-38-3 **90317-74-1** 182762-04-5, ZEP 7000B 263383-57-9, NEB 31 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(direct and indirect methods of supercrit, resist drying using

surfactant to replace rinse water with liquid carbon dioxide) ΙT 124-38-9, Carbon dioxide, processes

RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(liquid; direct and indirect methods of supercrit. resist drying using surfactant to replace rinse water with liquid carbon dioxide) THERE ARE 10 CITED REFERENCES AVAILABLE FOR THIS RECORD

- (1) Chittofrati, A; Prog Colloid Polym Sci 1989, V79, P218 HCAPLUS
- (2) Gallagher-Wetmore, P; Proc SPIE 1995, V2438, P694 HCAPLUS
  (3) Griffin, W; J Soc Cosmet Chem 1954, V5, P249
  (4) Hyatt, J; J Org Chem 1984, V49, P5097 HCAPLUS
  (5) Johnston, K; Science 1996, V271, P624 HCAPLUS
  (6) Named Company C
- (6) Namatsu, H; Appl Phys Lett 1995, V66, P2655 HCAPLUS (7) Namatsu, H; J Vac Sci Technol B 2000, V18, P780 HCAPLUS
- (8) Namatsu, H; Microelectron Eng 1998, V46, P129 (9) Newman, D; J Supercrit Fluids 1993, V6, P205 HCAPLUS (10) Ross, S; J Phys Chem 1959, V63, P1671 HCAPLUS IT 90317-74-1

RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(direct and indirect methods of supercrit. resist drying using surfactant to replace rinse water with liquid carbon dioxide)

90317-74-1 HCAPLUS RN

Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX NAME)

$$F-CF_2-CO_2H$$
 0-  $(C_3F_6)$  -  $n$  0-  $(CF_2)_3-F$ 

ANSWER 15 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN 2000:842181 HCAPLUS L24

134:29810 DN

ED Entered STN: 01 Dec 2000

- Aqueous dispersions of fluoropolymers and their production using ΤI fluorinated surfactants
- IN Morgan, Richard Alan; Jones, Clay Woodward; Hirvnak, Jeffrey; Treat, Theodore
- PA E. I. Du Pont de Nemours & Co., USA

PCT Int. Appl., 35 pp. S<sub>0</sub>

CODEN: PIXXD2

DT Patent

LA English

IC ICM C08F014-18

35-4 (Chemistry of Synthetic High Polymers)

FAN.	CNT	NO.	SS 1	KIND  A1		DATE 20001130			APPLICATION NO.					DATE					
ΡI	WO	2000071590 W: CU, JP								WO 2000-US14009					20000519				
			AT, PT.	ВE,	CH,	CY,	DE	, DK,	ES,	FI,	FR,	GB,	GR,	IE,	IT,	LU,	MC,	NL,	
	EP 1189953				A1		20020327			EP 2000-936159					20000519				
	EP	1189	1189953			B1		20040714											
	•	R:	AT, IE.		CH,	DE,	DK	, ES,	FR,	GB,	GR,	IT,	LI,	LU,	NL,	SE,	MC,	PT,	
	JP	2003500495				T2	T2		20030107		JP 2000-619980				20000519				
PRAI	ŬS	1999	-135	074P		P		1999	0520		•								
	WO	2000	-US1	4009		W		2000	0519										
CLAS	S																		
PAT	ENT	NO.		CLA	SS	PATE	NT	FAMIL	Y CL	ASS I	FICA	TION	COD	ES					

WO 2000071590 ICM C08F014-18

Aqueous dispersion polymerization of fluoromonomers is improved by using a combination of fluorosurfactants, one of which is a perfluoropolyether carboxylic acid or salt. In an example, hexafluoropropylene is copolymd. with tetrafluoroethylene in water containing Zonyl FS-62 (sulfo) and Krytox 157 FSH (carboxy) surfactants. Reaction time was reduced by incorporation of the second surfactant.

dispersion polymn fluoromonomer carboxylated fluorosurfactant; fluoropolymer prepn aq carboxylated fluorosurfactant

```
Surfactants
         (anionic; aqueous dispersion polymerization of fluoromonomers using fluorinated
         anionic surfactants)
IT
     Polymerization
         (dispersion, radical; aqueous dispersion polymerization of fluoromonomers using
         fluorinated anionic surfactants)
     Polyethers, uses
     Polyoxyalkylenes, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
         (fluorine-containing, surfactants; aqueous dispersion polymerization of fluoromonomers
         using fluorinated anionic surfactants).
     Fluoropolymers, preparation
     RL: IMF (Industrial manufacture); PREP (Preparation)
         (from aqueous dispersion polymerization of fluoromonomers using fluorinated
        anionic surfactants)
     Fluoropolymers, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
         (polyether-, surfactants; aqueous dispersion polymerization of fluoromonomers
        using fluorinated anionic surfactants)
     Fluoropolymers, uses
     RL: TEM (Technical or engineered material use); USES (Uses)
         (polyoxyalkylene-, surfactants; aqueous dispersion polymerization of
        fluoromonomers using fluorinated anionic surfactants)
     9002-84-0P, PTFE 25067-11-2P, Hexafluoropropylene-tetrafluoroethylene
                  26425-79-6P, Perfluoro(methyl vinyl ether)-tetrafluoroethylene 31784-04-0P, Perfluoro(ethyl vinyl ether)-tetrafluoroethylene 63654-40-0P, Hexafluoropropylene-perfluoro(ethyl vinyl
     copolymer
     copolymer
     copolymer
     ether)-tetrafluoroethylene copolymer 204270-08-6P, Perfluoro(ethyl vinyl
     ether)-perfluoro(methyl vinyl ether)-tetrafluoroethylene copolymer
     RL: IMF (Industrial manufacture); PREP (Preparation)
         (from aqueous dispersion polymerization of fluoromonomers using fluorinated
        anionic surfactants)
     3825-26-1, Ammonium perfluorooctanoate 27619-97-2 90317-74-1
     111019-20-6, Zonyl TBS 120895-92-3, Demnum SH 196623-59-3, Fluorolink
     RL: TEM (Technical or engineered material use); USES (Uses)
         (surfactant; aqueous dispersion polymerization of fluoromonomers using fluorinated
        anionic surfactants)
RE. CNT
               THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD
   Ausimont Spa; EP 0771823 A 1997 HCAPLUS
(2) Du Pont; EP 0006346 A 1980 HCAPLUS
(3) Du Pont; EP 0248446 A 1987 HCAPLUS
(4) Gore & Ass; WO 9622313 A 1996 HCAPLUS
     90317-74-1
     RL: TEM (Technical or engineered material use); USES (Uses)
         (surfactant; aqueous dispersion polymerization of fluoromonomers using fluorinated
        anionic surfactants)
     90317-74-1 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-\omega-(heptafluoropropoxy)- (9CI) (CA INDEX
         0-(C_3F_6) -\frac{1}{n} 0-(CF_2)_3-F
    ANSWER 16 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
     2000:790851 HCAPLUS
AN
DN
     134:71961
ED
     Entered STN: 12 Nov 2000
     Free Radical Polymerization of Methyl Methacrylate in Supercritical Carbon
     Dioxide Using a Pseudo-Graft Stabilizer: Effect of Monomer, Initiator, and
     Stabilizer Concentrations
```

Christian, Paul; Giles, Matthew R.; Griffiths, Rhiannon M. T.; Irvine,

Derek J.; Major, Richard C.; Howdle, Steven M.

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School of Chemistry, University of Nottingham, Nottingham, NG7 2RD, UK
     Macromolecules (2000), 33(25), 9222-9227
CODEN: MAMOBX; ISSN: 0024-9297
SO
     American Chemical Society
DT
     Iournal
     English
LA
CC
     35-4 (Chemistry of Synthetic High Polymers)
     This paper describes the free radical polymerization of Me methacrylate (MMA) in
     supercrit. carbon dioxide (scCO2) using a com. available acid-terminated
     perfluoropolyether (Krytox 157FSL) as a polymerization stabilizer. We have
     investigated the effect of varying the concns. of monomer, initiator, and
     stabilizer upon the mol. weight and morphol. of the resultant poly (Me
     methacrylate). The results obtained are compared to those observed for other
     stabilizers used for polymerization in scCO2. Krytox 157 FSL is shown to be an effective stabilizer leading to discrete spherical particles with diams.
     in the range expected from dispersion polymerization Unusual morphologies are
     observed at high initiator concentration and at lower stabilizer concentration
     Surprisingly, high yields of polymer are still formed even at very low
     concns. of stabilizer near 10-4 wt% with respect to monomer.
     Me methacrylate polymn supercrit carbon dioxide dispersion stabilizer;
     morphol polymethyl methacrylate stabilizer supercrit carbon dioxide
     Dispersing agents
     Particle size distribution
     Polymer morphology
         (effect of monomer, initiator, and stabilizer concns. on the free
        radical polymerization of me methacrylate in supercrit. carbon dioxide using a
        pseudo-graft stabilizer)
     Polyethers, uses
     RL: NUU (Other use, unclassified); USES (Uses)
        (perfluoro; effect of monomer, initiator, and stabilizer concns. on the free radical polymerization of me methacrylate in supercrit. carbon dioxide
        using a pseudo-graft stabilizer)
     Fluoropolymers, uses
IT.
     RL: NUU (Other use, unclassified); USES (Uses)
         (polyether-; effect of monomer, initiator, and stabilizer concns. on
        the free radical polymerization of me methacrylate in supercrit. carbon
        dioxide using a pseudo-graft stabilizer)
IT
     Polymerization catalysts
        (radical; effect of monomer, initiator, and stabilizer concns. on the
        free radical polymerization of me methacrylate in supercrit. carbon dioxide
        using a pseudo-graft stabilizer)
IT
        (supercrit.; effect of monomer, initiator, and stabilizer concns. on
        the free radical polymerization of me methacrylate in supercrit. carbon
        dioxide using a pseudo-graft stabilizer)
IΤ
     90317-74-1, Krytox 157FSL
     RL: NUU (Other use, unclassified); USES (Uses)
        (dispersion stabilizer; effect of monomer, initiator, and stabilizer
        concns. on the free radical polymerization of me methacrylate in supercrit.
        carbon dioxide using a pseudo-graft stabilizer)
IT
     9011-14-7P, Poly(methyl methacrylate)
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
        (effect of monomer, initiator, and stabilizer concns. on the free
        radical polymerization of Me methacrylate in supercrit. carbon dioxide using a
        pseudo-graft stabilizer)
     78-67-1, AIBN RL: CAT (Catalyst use); USES (Uses)
        (effect of monomer, initiator, and stabilizer concns. on the free
        radical polymerization of me methacrylate in supercrit. carbon dioxide using a
        pseudo-graft stabilizer)
     124-38-9, Carbon dioxide, uses
     RL: NUU (Other use, unclassified); USES (Uses)
        (effect of monomer, initiator, and stabilizer concns. on the free
        radical polymerization of me methacrylate in supercrit. carbon dioxide using a
        pseudo-graft stabilizer)
RE. CNT 24
              THERE ARE 24 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
   Barrett, K; Dispersion Polymerisation in Organic Media 1975
(1)
   Buback, M; J Supercrit Fluids 1995, V8, P119 HCAPLUS
(3) Canelas, D; Macromolecules 1996, V29, P2818 HCAPLUS
```

- (4) Canelas, D; Macromolecules 1997, V30, P5673 HCAPLUS (5) Christian, P; Macromolecules 2000, V33, P237 HCAPLUS (6) Christian, P; Polymer 2000, V41, P1251 HCAPLUS (7) Desimone, J; Science 1994, V265, P356 HCAPLUS
  (8) Giles, M; Macromolecules 2000, V33, P1996 HCAPLUS
  (9) Giles, M; Palmana 2000, V41, P1975 (9) Giles, M; Polymer 2000, V41, P1251 (10) Handa, P; J Polym Sci, Part B: Polym Phys 1996, V34, P2635 (11) Howdle, S; Chemical Synthesis Using Supercritical Fluids 1999, P147 **HCAPLUS**
- (12) Howdle, S; NATO Advanced Study Institute "Supercritical Fluids-Fundamentals for Application 1994, V273, P527 HCAPLUS
- (13) Hsiao, Y; Macromolecules 1995, V28, P8159 HCAPLUS (14) Kendall, J; Chem Rev 1999, V99, P543 HCAPLUS

(15) Lepilleur, C; Macromolecules 1997, V30, P745 HCAPLUS (16) Lora, M; Fluid Phase Equilib 1999, V157, P285 HCAPLUS

(17) McHugh, M; Supercritical Fluid Extraction; Principles and Practice 1994

(18) O'Neill, M; Macromolecules 1998, V31, P2838 HCAPLUS (19) O'Neill, M; Macromolecules 1998, V31, P2848 HCAPLUS

(20) Poliakoff, M; Angew Chem, Int Ed Engl 1995, V34, P1275 HCAPLUS

(21) Shaffer, K; Macromolecules 1996, V29, P2704 HCAPLUS

Sudol, D; Polymeric Dispersions: Principles and Applications 1997, P141

(23) Ute, K; Polymer 1995, V37, P1415 (24) Yong, T; Chem Commun 1997, P1811 HCAPLUS

90317-74-1, Krytox 157FSL

RL: NUU (Other use, unclassified); USES (Uses) (dispersion stabilizer; effect of monomer, initiator, and stabilizer concns. on the free radical polymerization of me methacrylate in supercrit. carbon dioxide using a pseudo-graft stabilizer)

RN 90317-74-1 HCAPLUS

Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-CN 1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX NAME)

$$F-CF_2-CO_2H$$
 0-  $(C_3F_6)$  -  $0$  0-  $(CF_2)_3-F$ 

L24 ANSWER 17 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN

1997:470691 HCAPLUS

- DN 127:196690
- Entered STN: 26 Jul 1997 ED
- ΤI Enhanced removal of radioactive particles from circuit boards by fluorinated surfactant solutions

Yam, C. S.; Kaiser, R.; Harling, O. K. Dep. Nuclear Eng., Mass. Inst. Technol., Cambridge, MA, 02139, USA CS Proceedings of the Annual Meeting of the Adhesion Society (1995), 18th, 62-65

CODEN: PAMSFE; ISSN: 1086-9506

- PB Adhesion Society
- DT Journal
- LA English
- 71-10 (Nuclear Technology)

Section cross-reference(s): 76

A laboratory scale ultrasonic decontamination system was developed for electronic circuit boards by using fluorinated surfactants. Particle removal capability of the perfluorinated liquid is better than that of CFC-113. Enhanced removal is obtained by adding 0.3 weight% of perfluorinated surfactant. High decontamination factors > 1000 are obtained in 1 h and removal rate after 1 h is >0. The cleaning process is nondestructive to electronic circuit boards. The process is cost effective and can be used for a wide variety of decontamination needs.

electronic circuit radioactive decontamination fluorinated surfactant

Perfluorocarbons

RL: NUU (Other use, unclassified); USES (Uses)

(Vertrel; enhanced removal of radioactive particles from circuit boards by fluorinated surfactant solns.)

IT Printed circuit boards Radioactive decontamination (enhanced removal of radioactive particles from circuit boards by fluorinated surfactant solns.) IT Surfactants (fluorosurfactants; enhanced removal of radioactive particles from circuit boards by fluorinated surfactant solns.) 90317-74-1, Krytox 157FS(L) RL: MOA (Modifier or additive use); NUU (Other use, unclassified); USES (enhanced removal of radioactive particles from circuit boards by fluorinated surfactant solns.) 335-57-9, Pf-5070 RL: NUU (Other use, unclassified); USES (Uses) ΙT (enhanced removal of radioactive particles from circuit boards by fluorinated surfactant solns.) RE. CNT 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD RE (1) Kaiser, R; US 4711256 1987 Kaiser, R; Draft Final Report NRC-04-92-109, Prepared for U S Nuclear Regulatory Commission 1993, NUREG/CG 6081 (3) Kaiser, R; Particles on Surface 4: Detection, Adhesion and Removal 1993 90317-74-1, Krytox 157FS(L) RL: MOA (Modifier or additive use); NUU (Other use, unclassified); USES (Uses) (enhanced removal of radioactive particles from circuit boards by fluorinated surfactant solns.) 90317-74-1 HCAPLUS RN Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]],  $\alpha$ -(1-carboxy-1, 2, 2, 2-tetrafluoroethyl)-@-(heptafluoropropoxy)- (9CI) (CA INDEX

$$F-CF_2-\begin{bmatrix} CO_2H \\ -CF_2 \end{bmatrix} = 0 - (C_3F_6) - \frac{1}{n} = 0 - (CF_2)_3 - F$$

ANSWER 18 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN 1995:262021 HCAPLUS 123:33744 DN ED Entered STN: 24 Dec 1994. Inverse emulsion polymerization of acrylamide in supercritical carbon ΤI dioxide. [Erratum to document cited in CA120:55125] All Adamsky, F. A.; Beckman, E. J. Dep. Chem. Eng., Univ. Pittsburgh, Pittsburgh, PA, 15261, USA Macromolecules (1994), 27(18), 5238 SO CODEN: MAMOBX; ISSN: 0024-9297 PB American Chemical Society DT Journal English LA CC 35-4 (Chemistry of Synthetic High Polymers) Section cross-reference(s): 46 The errors were not reflected in the abstract or the index entries. erratum inverse emulsion polymn acrylamide surfactant; inverse emulsion polymn acrylamide surfactant erratum; supercrit carbon dioxide acrylamide polymn erratum ĪΤ Surfactants (fluorinated, preparation of, for inverse emulsion polymerization of acrylamide in supercrit. carbon dioxide (Erratum)) Polymerization (inverse emulsion, of acrylamide in supercrit. carbon dioxide, fluorinated surfactant for (Erratum)) 124-38-9, Carbon dioxide, reactions RL: RCT (Reactant); RACT (Reactant or reagent) ΙT (inverse emulsion polymerization of acrylamide in (Erratum)) 90999-75-0P IT RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT

```
(Reactant or reagent)
        (preparation and amidation of (Erratum))
IT
     53789-69-8P
     RL: SPN (Synthetic preparation); PREP (Preparation)
        (preparation of, for surfactants for inverse emulsion polymerization of acrylamide
        in supercrit. carbon dioxide (Erratum))
IT
     9003-05-8P
     RL: SPN (Synthetic preparation); PREP (Preparation)
        (preparation of, in inverse emulsion in supercrit. carbon dioxide,
        fluorinated surfactant for (Erratum))
     90317-74-1
IT
     RL: RCT (Reactant); RACT (Reactant or reagent)
        (reaction with thionyl chloride of (Erratum))
     25038-02-2DP, Hexafluoropropylene oxide homopolymer, amide
     group-terminated
     RL: SPN (Synthetic preparation); PREP (Preparation)
        (surfactants, for inverse emulsion polymerization of acrylamide in supercrit.
        carbon dioxide (Erratum))
     90999-75-0P
IT
     RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
     (Reactant or reagent)
        (preparation and amidation of (Erratum))
     90999-75-0 HCAPLUS
RN
CN
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], \alpha-[1-
     (chlorocarbonyl)-1, 2, 2, 2-tetrafluoroethyl]-w-(heptafluoropropoxy)-
     (9CI) (CA INDEX NAME)
```

$$C1-C$$
 $F-CF_2-C$ 
 $O-(C_3F_6)$ 
 $n$ 
 $O-(CF_2)_3-F$ 

$$F-CF_2-CO_2H - O-(C_3F_6) - O-(CF_2)_3-F$$

```
ANSWER 19 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
AN
     1995:5307 HCAPLUS
DN
     122:12529
     Entered STN: 08 Nov 1994
ED
     Phase behavior of fluoroether-functional amphiphiles in supercritical
     carbon dioxide
     Newman, D. A.; Hoefling, T. A.; Beitle, R. R.; Beckman, E. J.; Enick, R.
     Dep. Chem. Eng., Univ. Pittsburgh, Pittsburgh, PA, 15261, USA
     Journal of Supercritical Fluids (1993), 6(4), 205-10
SO
     CODEN: JSFLEH; ISSN: 0896-8446
DT
     Journal
     English
LA
     46-3 (Surface Active Agents and Detergents)
CC
     Results with Krytox 157-based fluoroether-functional amphiphiles show that
     solubility is possible in supercrit. CO2. Apparently, there are several
     competing effects that determine the solubility of these materials in CO2:
     increasing mol. weight tends to drive the cloud-point curve to higher
     pressures, yet, addition of CO2-philic fluoroether groups and branching of
     the CO2-philic tails works to depress the cloud-point curve to lower
     pressures. Further, increasing the polarity of the polar head group
     induces the cloud-point curve to move to higher pressures.
     Fluoroether-functional amphiphiles permit extraction of thymol blue from aqueous
     solution into CO2.
ST
     surfactant anionic fluoropolymer polyether; supercrit carbon dioxide
     surfactant soly
IT
    Cloud point
        (phase behavior of fluoroether-functional amphiphiles in supercrit.
        carbon dioxide)
IT
     Surfactants
        (anionic, phase behavior of fluoroether-functional amphiphiles in
        supercrit. carbon dioxide)
IT
     Polyethers, preparation
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
        (carboxy- and fluorine-containing, salts; phase behavior of
        fluoroether-functional amphiphiles in supercrit. carbon dioxide)
IT
     Fluoropolymers
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
        (polyether-, carboxy-containing, salts; phase behavior of
        fluoroether-functional amphiphiles in supercrit. carbon dioxide)
ΙT
     124-38-9, Carbon dioxide, properties
     RL: PRP (Properties)
        (phase behavior of fluoroether-functional amphiphiles in supercrit.
        carbon dioxide)
     154-42-7DP, 2-Aminopurine-6-thiol, salts of carboxy-containing fluoropolymer-polyethers 452-06-2DP, 2-Aminopurine, salts of
     carboxy-containing fluoropolymer-polyethers
                                                    61414-25-3DP, salts with
     carboxy-containing fluoropolymer-polyethers 90317-74-1DP, Krytox
     157FS(L), salts
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
        (phase behavior of fluoroether-functional amphiphiles in supercrit.
        carbon dioxide)
     90317-74-1DP, Krytox 157FS(L), salts
IT
     RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
        (phase behavior of fluoroether-functional amphiphiles in supercrit.
        carbon dioxide)
     90317-74-1 HCAPLUS
RN
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX
```

$$F-CF_2-CO_2H$$
  $O-(C_3F_6)$   $O-(CF_2)_3-F$ 

L24 ANSWER 20 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN

```
1994:55125 HCAPLUS
     120:55125
DN
ED
     Entered STN: 05 Feb 1994
     Inverse emulsion polymerization of acrylamide in supercritical carbon
ΤI
AU
     Adamsky, F. A.; Beckman, E. J.
     Dep. Chem. Eng., Univ. Pittsburgh, Pittsburgh, PA, 15261, USA Macromolecules (1994), 27(1), 312-14
CS
S<sub>0</sub>
     CODEN: MAMOBX; ISSN: 0024-9297
     Iournal
     English
     35-4 (Chemistry of Synthetic High Polymers)
     Section cross-reference(s): 46
     Inverse emulsion polymerization of acrylamide was performed using supercrit. CO2
     as the continuous phase to produce ultra-high mol.-weight linear homopolymer.
     A new surfactant, highly soluble in supercrit. CO2, was synthesized to create
     the inverse emulsions. Data are presented for both surfactant and
     homopolymer characterization.
ST
     inverse emulsion polymn acrylamide surfactant; supercrit carbon dioxide
     acrylamide polymn
IT
     Surfactants
         (fluorinated, preparation of, for inverse emulsion polymerization of acrylamide in
        supercrit. carbon dioxide)
IT
     Polymerization
         (inverse emulsion, of acrylamide in supercrit. carbon dioxide,
        fluorinated surfactant for)
     124-38-9, Carbon dioxide, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
IT
         (inverse emulsion polymerization of acrylamide in)
IT
     90999-75-0P
     RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
     (Reactant or reagent)
         (preparation and amidation of)
     53789-69-8P
     RL: SPN (Synthetic preparation); PREP (Preparation)
         (preparation of, for surfactants for inverse emulsion polymerization of acrylamide
        in supercrit. carbon dioxide)
     9003-05-8P, Polyacrylamide
IΤ
     RL: SPN (Synthetic preparation); PREP (Preparation)
         (preparation of, in inverse emulsion in supercrit. carbon dioxide,
        fluorinated surfactant for)
     90317-74-1
IT
     RL: USES (Uses)
         (reaction with thionyl chloride of)
ΙT
     25038-02-2D, Hexafluoropropylene oxide homopolymer, amide group-terminated
     RL: USES (Uses)
         (surfactants, for inverse emulsion polymerization of acrylamide in supercrit.
        carbon dioxide)
     90999-75-0P
     RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
     (Reactant or reagent)
         (preparation and amidation of)
     90999-75-0 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], \alpha-[1-
     (chlorocarbonyl)-1, 2, 2, 2-tetrafluoroethyl]-w-(heptafluoropropoxy)-
     (9CI) (CA INDEX NAME)
```

## 53789-69-8P

RL: SPN (Synthetic preparation); PREP (Preparation) (preparation of, for surfactants for inverse emulsion polymerization of acrylamide in supercrit. carbon dioxide)

IT 90317-74-1
RL: USES (Uses)
(reaction with thionyl chloride of)

RN 90317-74-1 HCAPLUS
CN Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX
NAME)

$$F-CF_2-CO_2H - O-(C_3F_6) - O-(CF_2)_3-F$$

ANSWER 21 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN AN 1991:663987 HCAPLUS DN 115:263987 Entered STN: 14 Dec 1991 ED Surface activity of fluorine-containing surfactants in polar solvents and water-organic mixtures AU Sharovarnikov, A. F.; Teplov, G. S. Vysshaya Inzh. Pozharno-Tekhnol. Shk., Moscow, USSR CS S<sub>0</sub> Kolloidnyi Zhurnal (1991), 53(5), 949-54 CODEN: KOZHAG; ISSN: 0023-2912 DT Journal LA Russian CC 66-1 (Surface Chemistry and Colloids) Section cross-reference(s): 46 The surface active properties of RFC(0)R' (derivs. of perfluoroaliph. AB acids (F(CF2)nCOOH), monochloroperfluoroaliph. acids (ClCF2)nCOOH), CF3(CF2)20(CF(CF3)CF20)n(CF(CF3)COOH (I), and [RF C(0)NH(C3H6)NMe2R']X (X = halide; RF = fluorine-containing radical; R' = unfluorinated N-containing radical, OH, or cation; R' = H, Me, Et, Et0, OAc, (Me0)SO3)) were studied in alc. or aqueous alc. solns. Compds. of type I exhibit surface activity in both aqueous and neat alc. solns. The free energy of transfer of 1 CH2 or 1 CF2 group from bulk solvent to the micella phase was calculated from the dependence of the cmc. of I in EtOH on the number of CF(CF3)CF20 links in the mol. ST fluorine contg surfactant surface activity alc Micelles (critical concentration of, in fluorine-containing surfactant solns. in alcs. or aqueous alcs.) IT Amides, properties RL: PRP (Properties) (fluoroalkyl, surface activity of, in alcs. or aqueous alcs.) IT Surface activity (of fluorine-containing surfactants, in alcs. or aqueous alcs.) IT Free energy (of transfer, of fluoromethylene group between micelles and neat ethanol phase) Quaternary ammonium compounds, properties RL: PEP (Physical, engineering or chemical process); PRP (Properties); PROC (Process) (surface activity of, in alcs. or aqueous alcs.)

```
Perfluoro compounds
     RL: PEP (Physical, engineering or chemical process); PRP (Properties);
     PROC (Process)
         (carboxylic acids, surface activity of, in alcs. or aqueous alcs.)
     Carboxylic acids, properties
     RL: PEP (Physical, engineering or chemical process); PRP (Properties);
     PROC (Process)
         (perfluoro, surface activity of, in alcs. or aqueous alcs.)
     64-17-5, Ethanol, properties 67-63-0, 2-Propanol, properties
     Butyl alcohol, properties
     RL: PRP (Properties)
         (surface activity in, of fluorine-containing surfactants)
                   69306-54-3 90317-74-1
IT
     16432-82-9
                                             137476-16-5
                                                             137476-17-6
     137476-18-7 RL: PEP (Physical, engineering or chemical process); PRP (Properties);
     PROC (Process)
         (surface activity of, in alcs. or aqueous alcs.)
     90317-74-1
IT
     RL: PEP (Physical, engineering or chemical process); PRP (Properties);
     PROC (Process)
         (surface activity of, in alcs. or aqueous alcs.)
     90317-74-1 HCAPLUS
RN
CN
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-ω-(heptafluoropropoxy)- (9CI) (CA INDEX
     NAME)
              -0-(C_3F_6) -\frac{1}{n} 0-(CF_2)_3-F
L24
     ANSWER 22 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
     1987:432064 HCAPLUS
AN
DN
     107:32064
     Entered STN: 25 Jul 1987
ED
ΤI
     Magnetic fluid
     Sugano, Takao
IN
     NOK Corp., Japan
Jpn. Kokai Tokkyo Koho, 4 pp.
PA
S<sub>0</sub>
     CODEN: JKXXAF
DT
     Patent
LA
     Japanese
IC
     ICM H01F001-12
     ICS
          C10M169-04
ICA
     C09K003-10
     C10M169-04, C10M105-54, C10M125-10; C10N040-14
ICI
CC
     77-8 (Magnetic Phenomena)
FAN. CNT 1
     PATENT NO.
                           KIND
                                   DATE
                                                APPLICATION NO.
                                                                          DATE
     JP 61263202
                            A2
                                                JP 1985-103697
                                                                          19850517
                                   19861121
     JP 04076484
                            B4
                                   19921203
PRAI JP 1985-103697
                                   19850517
CLASS
PATENT NO.
                          PATENT FAMILY CLASSIFICATION CODES
                  CLASS
 JP 61263202
                  ICM
                          H01F001-12
                          C10M169-04
                  ICS
                          C09K003-10
                  ICA
     ICI C10M169-04, C10M105-54, C10M125-10; C10N040-14
A magnetic fluid having a good dispersion stability consists of magnetic
AB
     fine powders dispersed in perfluoroether-type base oil using a
     perfluoroether-type surfactant as a dispersing agent. A method for the
     preparation of the fluid involves the following steps: (1) preparing an
     organic-solvent suspension of the magnetic powders from an aqueous suspension which has been prepared by a wet method; (2) adding the perfluoroether-type
```

surfactant and base oil; and (3) removing the organic solvent.

```
perfluoroether surfactant dispersion agent ferrofluid
IT
     Ferrofluids
        (perfluoroether surfactant as dispersion agents for)
IT
     Dispersing agents
       Surfactants
        (perfluoroethers, for magnetic fluids)
     Polyethers, uses and miscellaneous
     RL: PRP (Properties)
        (perfluoro, surfactants, as dispersion agents for magnetic fluids)
     Perfluoro compounds
     RL: PRP (Properties)
        (polyethers, surfactants, as dispersion agents for magnetic fluids)
IT
     52700-35-3
     RL: PRP (Properties)
        (magnetic fluids containing base oils of, dispersion agent for)
     90317-74-1 108072-64-6
     RL: PRP (Properties)
        (surfactants, as dispersion agents for magnetic fluids)
     90317-74-1
IT
     RL: PRP (Properties)
        (surfactants, as dispersion agents for magnetic fluids)
     90317-74-1 HCAPLUS
     Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-
     1, 2, 2, 2-tetrafluoroethyl)-\omega-(heptafluoropropoxy)- (9CI) (CA INDEX
     NAME)
```

$$F-CF_2-CO_2H$$
 $O-(C_3F_6)-O-(C_{F_2})_3-F$ 

```
L24 ANSWER 23 OF 23 HCAPLUS COPYRIGHT 2005 ACS on STN
      1972:406026 HCAPLUS
AN
      77:6026
      Entered STN: 12 May 1984
ED
ΤI
      Esters of hexafluoropropylene oxide polymer acids and polyalkylene glycols
IN
      Bartlett, Philip L.
PA
      du Pont de Nemours, E. I., and Co.
S0
      U.S., 4 pp.
      CODEN: USXXAM
DT
      Patent
LA
      English
IC
      CO7C
INCL 260484000R
      35-3 (Synthetic High Polymers)
CC
FAN. CNT 1
      PATENT NO.
                                 KIND
                                          DATE
                                                           APPLICATION NO.
                                                                                          DATE
      US 3644492
                                           19720222
                                                           US 1969-846238
                                                                                          19690730
PRAI US 1969-846238
                                           19690730
CLASS
 PATENT NO.
                       CLASS
                                PATENT FAMILY CLASSIFICATION CODES
 US 3644492
                       IC
                                CO7C
                       INCL
                                260484000R
                                560/184,000; 516/074,000; 562/586,000; 562/849,000
 US 3644492
                       NCL
      The esters (I, R1 = perfluoropropyl, n = 1-36, R2 = ethylene or propylene
      radical, R3, R4, R5 = H or Me, and x = 5-45) were prepared by treating an acid
      fluoride with a polyalkylene glycol in the presence of an acid acceptor;
      an acyl fluoride-polyalkylene glycol adduct with an alkylene oxide; or a
      fluorocarboxylic acid with an alkylene oxide. I were useful in fire
      fighting and permitted the spreading of a film of water or foam on the surface of a liquid hydrocarbon. Thus, CF3(CF2)20[CF(CF3)CF20]8CF(CF3)COF was mixed with 1, 1, 2-trichloro-1, 2, 2-trifluoroethane (II), triethylamine, Carbowax-350 [heptakis(ethylene glycol) monomethyl ether] [4437-01-8], and addnl. II, to give I (R1 = CF3CF2CF2, n = 8, R2 = CH2CH2, R3 = R4 = R5 = H, x = 6) [34834-37-2] used in H2O emulsions.
```

ST perfluoropropylene oxide polyesterification; polyalkylene glycol polyesterification; fluoropropylene oxide polyesterification; emulsifier fluoro polyester; fire extinguishing emulsions

IT Fire

(extinguishing of, fluorinated polyesters for use in)

IT Esters, preparation

RL: PREP (Preparation)

(of fluorinated, as emulsifiers and surfactants)

IT Emulsifying agents

Surfactants

(polyalkylene glycol esters of fluorinated carboxylic acids as)

(polyalkylene glycol esters of fluorinated carboxylic acids as)
IT 37208-48-3 37208-51-8 37208-52-9 37494-04-5 37503-46-1
37541-11-0 37541-12-1 37871-32-2 37871-33-3
RL: USES (Uses)

(emulsifiers and surfactants)

CN Poly[oxy[trifluoro(trifluoromethyl)-1, 2-ethanediyl]], α-(1-carboxy-1, 2, 2, 2-tetrafluoroethyl)-α-(heptafluoropropoxy)-, ester with α-hydro-α-methoxypoly(oxy-1, 2-ethanediyl) (9CI) (CA INDEX NAME)

=> b home FILE 'HOME' ENTERED AT 12:22:52 ON 03 MAY 2005